Document made available under the Patent Cooperation Treaty (PCT)

International application number: PCT/NL05/000129

International filing date: 22 February 2005 (22.02.2005)

Document type: Certified copy of priority document

Document details: Country/Office: US

Number: 60/546,165

Filing date: 23 February 2004 (23.02.2004)

Date of receipt at the International Bureau: 25 April 2005 (25.04.2005)

Remark: Priority document submitted or transmitted to the International Bureau in

compliance with Rule 17.1(a) or (b)



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United States Patent and Trademark Office

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APPLICATION NUMBER: 60/546,165 FILING DATE: February 23, 2004

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Additional inventors are being named on the separately numbered sheets attached hereto .							
TITLE OF THE INVENTION (500 characters max) System, Method, and Apparatus to Separate Dose and Focus Based on Scatterometry Data							
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X Specification Number of Pages 45 CD(s), Number X Drawing(s) Number of Sheets 0* X Application Data Sheet. See 37 CFR 1.76]	
METHOD OF PAYMENT OF FILING FEES FOR THIS PROVISIONAL APPLICATION FOR PATENT Applicant claims small entity status. See 37 CFR 1.27. A check or money order is enclosed to cover the filing fees The Commissioner is hereby authorized to charge filing fees or credit any overpayment to Deposit Account Number: Payment by credit card. Form PTO-2038 is attached.							
The invention was made by an agency of the United States Government or under a contract with an agency of the United States Government. X No. Yes, the name of the U.S. Government agency and the Government contract number are:							
Respectfully submitted, (1) Date Feb 23, 2004							
SIGNATURE ————			REGISTRATION NO. (if appropriate) 41818				
TYPED or PRINTED NAME Kerry Hartman					081468-0308	434	

USE ONLY FOR FILING A PROVISIONAL APPLICATION FOR PATENT

This collection of information is required by 37 CFR 1.51. The information is used by the public to file (and by the PTO to process) a provisional application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 8 hours to complete, including gathering, preparing, and submitting the complete provisional application to the PTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S.D Department of Commerce, Washington, D.C. 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Box Provisional Application, Assistant Commissioner for Patents, Washington, D.C. 20231.

*Color figures integrated with text.

Attorney Docket No. 081468-0308434 Client Reference: P-1823.000-US **PATENT**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Hans van der Laan

Application No.:

NEW

Confirmation No:

Filed:

February 23, 2004

Group No.: Examiner

For:

System, Method, and Apparatus to Separate Dose and Focus Based on Scatterometry Data

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

APPLICATION DATA SHEET 37 C.F.R. § 1.76

BIBLIOGRAPHIC DATA

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Customer No.: 00909

3. Application information

Title of Invention: System, Method, and Apparatus to Separate Dose and Focus Based on Scatterometry Data

Docket number assigned to this application: 081468-0308434

Suggested Classification:

Class:

Subclass:

Technology Center to which subject matter is assigned:

Total number of drawing sheets: 0 (color figures integrated with text)

Type of application: Provisional

Secrecy order under § 5.2: This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

Application Date Sheet--page 1 of 2

4. Representative information

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Extent of interest of assignee in application: Entire right, title and interest.

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Provisional U.S. Patent Application: SYSTEM, METHOD, AND APPARATUS TO SEPARATE DOSE AND FOCUS BASED ON SCATTEROMETRY DATA Summary

A scatterometry method is described which can separate focus and dose errors made during exposure. The focus data is correlated to other techniques. A method according to one embodiment of the invention, based on Principal Component Regression, comprises two steps:

1. A calibration FEM is exposed, readout by the scatterometer, and the measurement results are used to build a model of focus/dose vs. spectra. This model is directly based on the scatterometry spectra. Potential advantages may include that no knowledge of optical properties of materials is required and that complex and time consuming building of libraries can be skipped.

2. The to-be-measured-wafers are read-out. Using the model, the recorded spectra are translated into focus and dose values. The calculation only takes a few seconds per wafer (1000 points).

The scatterometer can measure gratings in the scribe lane or directly structures in the chip, making the technique suitable for on-product monitoring and calibration. The accuracy (including repro) is better than 25nm (3σ) per single field point, which is comparable to that of FOCAL. Correlating scatterometry results with LVT (PreFoc) and Wafer map MA data concludes this. As an example, with this accuracy, Ry determination is better than 0.2μ rad (3σ) when using 75 measurement points.

Introduction

There are many techniques for focus calibration using test wafers: FOCAL, LQT (reticle with small prisms), phase shift focus monitor,..... They require a special mask, a special illumination setting or a focus meander for each measurement, disqualifying them for measurements on product wafers.

For focus measurements on product wafers, either on marks in the scribe lane or directly within the chip, only few techniques exist which are not very mature. A currently used technique is the measurement of Line-End-Shortening of test targets in the scribe lane, e.g. KLA MPX. This technique, however, does not contain information on the sign of focus and is therefore only suited for monitoring and not for correcting focus.

This memo shows how scatterometry can be used to measure focus. Two strong points for scatterometry are:

- There are no special requirements on mask type and/or illumination mode, i.e. it is directly suited for measurement of product wafers.
- The raw output of the scatterometer HW is one or more fine-structured spectra, the shape of
 which varies strongly with the line width and shape of the measured feature. This implies that the
 information content of scatterometry spectra is enormous. The expectation is that also focus
 information is present; the challenge is how to retrieve it.

The presented scatterometry technique is based on direct evaluation of spectra, by comparing them to spectra measured on a calibration FEM. This technique may reduce or eliminate standard scatterometry drawbacks like the need for forehand knowledge of optical properties of materials and the complex and time-consuming building of libraries. Furthermore, the technique is not limited to the standard 1D-structures, but also allows measurement of 2D-structures and even directly on product.

Further embodiments include taking into account dependencies on resist type and/or scatterometer type (polarized reflectometer, un-polarized reflectometer, or ellipsometer).

In principle, all focus applications are possible:

- · Focus calibration using test wafer
- Focus monitoring on product wafers (both scribe-lane and within chip)
- Focus calibration on product wafers (both scribe-lane and within chip)

A method according to an embodiment of the invention

The method includes a calibration step followed by measurement of product wafers. In the calibration step a FEM is exposed and the corresponding scatterometry spectra are measured. The second step is recording the scatterometry spectra for the product wafers. It may be desirable or necessary that both calibration and product measurements are performed for the identical structure and process conditions.

APPLICATION UNDER UNITED STATES PATENT LAWS

A	PPLICATION UNDER UNITED STAT	ES PATENT LAVS
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	Contain Mathed and American to Consult Days	and France Based on Coothernweeter But
nvention:	System, Method, and Apparatus to Separate Dose a	nd Focus Based on Scatterometry Data
nventor (s):	Hans van der Laan	
		Address communications to the correspondence address associated with our Customer No 00909 Pillsbury Winthrop LLP
		This is a:
		Provisional Application
		Regular Utility Application
	. 🗖	Continuing Application The contents of the parent are incorporated by reference
		PCT National Phase Application
		Design Application
		Reissue Application
		Plant Application
		Substitute Specification Sub. Spec Filed in App. No. /
		Marked up Specification re Sub. Spec. filed/
	SPECIFICATION	•

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The principle of this calibration is explained by Figure 1. It displays spectra belonging to the calibration FEM (left) and a spectrum originating from the product wafer (right). Most straightforward way-of-working would be searching for the best match between a product wafer spectrum and one of the spectra in the FEM-set. From the best match, the focus and dose values can be derived.

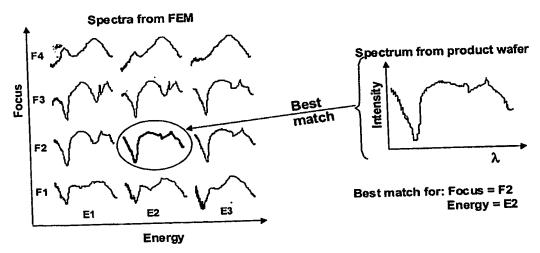


Figure 1 Spectra belonging to calibration FEM (left) and a spectrum originating from the product wafer (right). Finding the best match between spectra gives the focus and dose values.

For our analysis, however, we used a more sophisticated algorithm: Principal Component Regression (PCR). The principle is that each spectrum can be described by a sum of basic spectra or principal components (similar to Fourier analysis where each signal can be split up in its Fourier components). There are two advantages with respect to the straightforward method: 1. Smoothing of the noise in the calibration step (by limiting the number of principle components) and 2. Avoiding the discretization of the determined focus and dose values by using a regression technique (i.e. fit).

Experimental

Experiments were performed within the project "Correlation (de)focus vs. CDU".

Scanner + illum	AT:850, M8868, NA=0.8, σ=0.85/0.55		
Wafers	Full wafer exposures on four special MEMC wafers (A,B,C,D), deliberately made unflat.		
:-	In this memo, only data from wafers C and D have been analysed		
FEM Exposure	21x21 FEM: focus range –300 → 300nm, step 30nm dose range 22 → 32 mJ/cm², step 0.5 mJ/cm² To avoid processing influences, a mini FEM was exposed. Position on wafer: x = 60 → 90mm, y = -25 → 25mm		
	A section of 13x9 is used in the calibration step focus: -300 → 60nm, dose: 26 → 32 mJ/cm ²		
Wafer map, MA	Measurements in same run as the LVT exposures		
	Focus offset of –90nm to match scatterometry measurements		
LVT Full wafer	LVT exposures on the four MEMC wafers. After read-out, wafers were stripped and re-coated for the CDU exposures.		
exposure	Focus offset of –125nm to match scatterometry measurements		
CDU Full wafer	Exposed with Focus offset: -110nm Dose: 27.4mJ/cm ²		
Exposure	Dose: 27.4mJ/cm² Standard CDU layout, field size 26x33mm		
	CDU exposures on same chuck as LVT exposures		
	Exposures on the four MEMC-wafers		
Process	DUV42 (60nm) + PEK500 (330nm) + Aquatar6 (52nm), i.e. standard AT850 qualification process		
Reticle	ELM-SCAT-110, 455.6311.1i001		
Measurement grid	MA, 7×61 , $X = \pm 10.2$ mm, $Y = \pm 15.2$ mm LVT, 9×7 , $X = \pm 12.7$ mm, $Y = \pm 16.2$ mm		
Standard	Scat, 7 x 5, X = ±12.4mm, Y = ±15.4mm		
Structure	110nm isolated line (pitch 1;6, binary mask)		
Scatterometer	KLA-Tencor SpectraCD. Oblique incidence		

Figure 2 is a wafer map of the MEMC-C wafer measured by the Level Sensor. A number of 'holes', with a depth up to $0.5\mu m$, is visible. The area within the rectangle has been measured by scatterometry. The flatness of the other 3 wafers is similar but with the 'holes' at different locations.

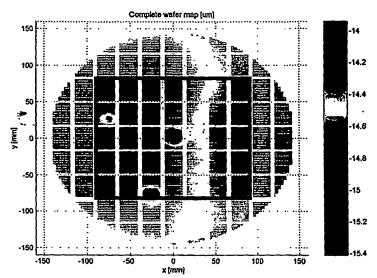


Figure 2 Wafer map for MEMC_C. The area within the box has been measured by scatterometry.

Results

As described in the section 'method', the spectra coming from the FEM wafer may be used to build the model. In this example, not all 21x21 spectra are used, but a subset containing 13 focus steps and 9 dose steps. Also in this example, the focus range chosen to be symmetrical around Best Focus, and the dose range is chosen to cover the expected dose variation.

One set of measures for the quality of the created model are the residue in focus and dose between the values set by the FEM and those given by the model. The residue for focus is 7nm (3 σ) and for dose 0.15% (3 σ).

Applying this model to the spectra from MEMC-C wafer results in the focus and dose distribution shown in Figure 3. The white spaces indicate missing data points¹. The focus errors over a large part of the wafer are small. Near the 'holes', second order focus errors across the field are seen, which the leveling system may not be able to correct.

The fields without 'holes' can be used to determine the intra-field fingerprint. The intra-field focus fingerprint should correlate with the focal plane, e.g. measured by FOCAL. For dose, the intra-field variation should correlate to the sum of dose uniformity and reticle fingerprint (in a later stage we will look at these intra-field correlations).

Furthermore, note that the inter-field dose fingerprint clearly shows across wafer gradient with dose increasing towards (+X,-Y).

¹ In these case the model could not determine the focus and dose values belonging to the spectrum, since the values were outside the calibration range

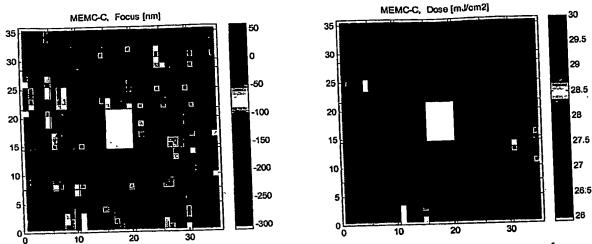


Figure 3 Full wafer Focus and Dose measurements by scatterometry on MEMC_C (area on wafer given by rectangle in Figure 2). The center field has been exposed differently and was therefore not read-out. The white squares indicate missing data points.

To verify the accuracy of the scatterometry results, correlation to other well-established methods was considered. For focus this will be discussed below, while for dose no reference technique was available and will be neglected in the remainder of this memo. Figure 4 shows focus errors, determined from the Wafer Map moving average values, MA (left) and scatterometry (right). The scatterometry data has been interpolated to the MA measurement grid for sake of comparison. A good correlation is seen.

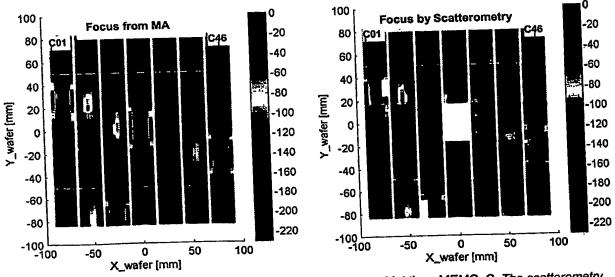
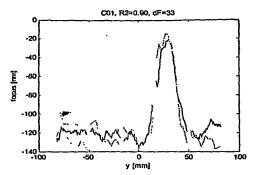


Figure 4 Focus measurements by MA (left) and scatterometry (right) on MEMC_C. The scatterometry data has been interpolated to the MA measurement grid.

Figure 5 compares two columns of the focus data obtained by MA and scatterometry as indicated in Figure 4. On the left, a typical example with a 3σ focus difference of 33nm. On the right, a better than typical example with a 3σ focus difference of 19nm. For both cases the correlation is very good, R²≥0.90. The figure also shows that there is a systematic intra-field difference between both techniques. The MA-values are always higher than the scatterometry values at the edge of the field. A difference can be expected since the lens and reticle contribution to focus may be present only in the scatterometry data.



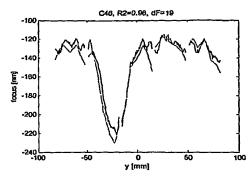
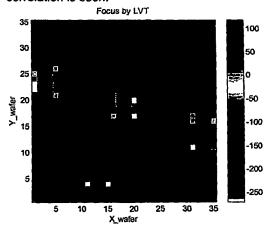


Figure 5 Focus measurements by MA (black trace) and scatterometry (red trace) for two columns of Figure 4, (MEMC_C). On the left, a typical example with a 3σ focus difference of 3nm (column 1). On the right, a good example with a 3σ focus difference of 19nm. For both cases the correlation is very good, $R^2 \ge 0.90$.

In Figure 6 the scatterometry data is compared to the next technique called Leveling Verification Test (LVT, on the PAS LQT). This test uses a distortion like reticle with a large number of small prisms, each glued above an alignment mark. The principle is that focus errors are translated into overlay errors. The LVT-data has been interpolated to the scatterometry measurement grid. Also here a good correlation is seen.



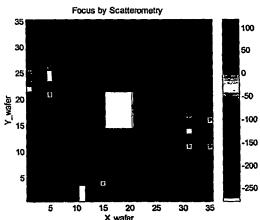
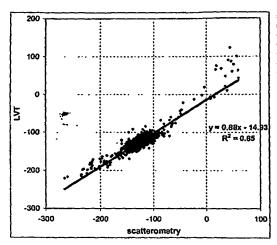


Figure 6 Focus measurements by LVT (left) and scatterometry (right) on MEMC_C. The LVT data has been interpolated to the scatterometry measurement grid.

Figure 7 shows the correlation plots of scatterometry with LVT and scatterometry with MA. The intrafield differences between both techniques have been removed, since they are different for each technique. The plots show a slope slightly below 1 (scatterometry measures a slightly larger focus variation) and a good correlation, R²>0.8.

For the large positive values in the LVT graph, larger deviations are found. Possibly these points are so far out-of-focus (BF is at -110nm) that the process is not very reproducible for 110nm isolated line imaging.

Note that the focus range for the Scatterometry – LVT correlation plot is larger than that for Scatterometry – MA. The reason is that the maximum X-field position is 10.2mm for MA compared to 12.4mm for Scatterometry, and the largest focus errors are found at the field edge.



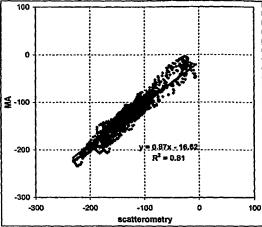


Figure 7 Correlation plot displaying the correlation Scatterometry-LVT and Scatterometry-MA for MEMC_C.

Table 1 summarizes the correlation results. It gives the differences in focus measured by LVT and scatterometry for two wafers and two types of scatterometry spectra $(\alpha/\beta)^2$. The correlation results are very similar for both wafers and do not depend strongly on the type of spectrum used. The correlation, expressed in 3σ -focus difference, seems to be better for MA. One should realize, however, that the focus range for the Scat/LVT correlation is larger than for MA (caused by the difference in measurement grid)

The upper limit for the scatterometry accuracy is given by the focus difference between the two best matching techniques (Scat. and MA). The real accuracy will be better since MA also has a certain inaccuracy and the wafer has been recoated in between the two measurements. The conclusion is that the accuracy (incl. repro) is better than 25nm (3σ)

	MA			LVT		
}	dF [nm 3σ]	slope	R ²	dF [nm 3σ]	slope	R ²
MEMC_C, a	26	0.87	0.81	36	0.88	0.85
β	25	0.93	0.77	36	0.87	0.76
MEMC_D, α	31	0.81	0.71	37	0.81	0.81
β	27	0.90	0.73	36	0.81	0.74
Average	27	0.88	0.75	36	0.85	0.79

Table 1 Focus differences between Scatterometry - MA (left) and Scatterometry - LVT (right). Correlation is presented as the 3σ -focus deviation between both techniques, and the regression slope and correlation coefficient R^2 .

A clue on the repro is given by Table 2. It shows the difference in focus is determined with either one of the spectra types. These values can be considered as a lower value for the repro. In the future, comparisons of focus measured with H and V will be done.

Focus difference between α- and β- spectra [nm]			
30	mean		

The KLA scatterometer is based on a ellipsometer, which simultaneously measures two polarization directions, resulting in two spectra, called α and β . All results up to now, however, have been only based on the α -specra.

MEMC_C	14	4.1
MEMC_D	_ 12	5.4

Table 2 Differences in focus determined with either one of the two scatterometry spectrum types (α or β). This intrinsic comparison shows a very good match.

Use of the Scatterometry Focus Technique

Figure 8 (left) shows the residuals from the LVT/Scat correlation for MEMC_C of Figure 7. On the right, a similar plot for MEMC_D. A patch like structure is seen, indicating that not all fields are exposed with exactly the same focus value. Differences up to 20nm are seen.

Another example is the determination of image tilt Ry. With a single point accuracy of 25nm (3 σ), Ry determination is better than 0.2 μ rad (3 σ) when using 75 measurement points.

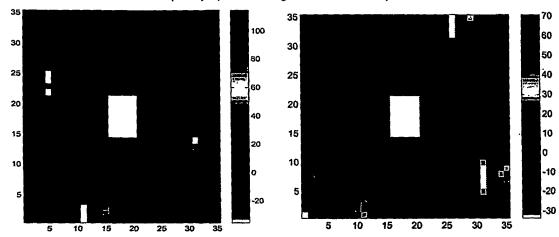


Figure 8 (Left) Residuals from the left part of Figure 7 plotted as function of wafer coordinates, data from MEMC_C. On the right, a similar plot for MEMC_D. The plot clearly shows that the focus differences between the LVT and scatterometry exposure varies from field to field.

Attachments

- (1) "Title of the Development," 2 pages with integrated color figures.
- (2) "Focus measurements with scatterometry," 22 pages with integrated color figures.
- (3) Spreadsheet referenced on page 8 of attachment (2), 10 pages.

Claims

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- 1. Method of determining parameters related to a lithographic apparatus comprising:
 - using a scatterometer to measure calibration spectra on a calibration focus-energy matrix (FEM);
- using a scatterometer to measure a spectrum of at least one diffractive structure of a substrate; and
 - analyzing the measured spectrum of the at least one diffractive structure; wherein said analyzing of the measured spectrum includes comparing the calibration spectra and the measured spectrum of the at least one diffractive structure.
 - 2. The method according to claim 1, wherein said analyzing includes deriving parameters to be determined by employing a regression technique.
- The method according to any of claims 1 and 2, wherein said analyzing includes
 applying a mathematical model which compares the calibration spectra on the calibration FEM with the measured spectrum on said substrate and derives the parameters to be determined by employing a regression technique.
- 4. A method according to claim 3, wherein said parameters to be determined at leastinclude focus and dose.
 - 5. A method according to any of claims 2-4, wherein the regression technique used by the mathematical model is principal component regression (PCR).
- 30 6. A method according to any of claims 1-5, wherein the substrate comprises a test wafer.

- 7. A method according to any of claims 1-6, wherein the substrate comprises a product wafer.
- 8. A method according to any of claims 1-7, wherein the at least one diffractive
 5 structure is either positioned within the chip or in the scribe-lane.
 - 9. A method of determining parameters, said method comprising:
 - using a scatterometer to measure calibration spectra on a calibration focus-energy matrix (FEM);
- using a scatterometer to measure a spectrum of at least one diffractive structure of a substrate; and

based on the calibration spectra and the measured spectrum of the at least one diffractive structure, obtaining values of parameters relating to a lithographic exposure procedure.

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- 10. The method according to claim 9, wherein said obtaining includes deriving parameters to be determined by employing a regression technique.
- 11. The method according to any of claims 9-10, wherein said obtaining includes applying a mathematical model which compares the calibration spectra on the calibration FEM with the measured spectrum on said substrate and derives the parameters to be determined by employing a regression technique.
- 12. A method according to any of claims 10-11, wherein the regression technique used by the mathematical model is principal component regression (PCR).
 - 13. A method according to any of claims 9–12, wherein said obtaining includes performing a principal component analysis on at least a portion of the calibration spectra.

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14. A method according to claim 13, wherein said obtaining includes constructing a model based on said principal component analysis.

- 15. A method according to any of claims 9-14, wherein said obtaining includes constructing a model based on at least a portion of the calibration spectra.
- 16. A method according to any of claims 9-15, wherein said parameters to be determined at least include focus and dose.
 - 17. A method according to any of claims 9-16, wherein the substrate comprises a test wafer.
- 18. A method according to any of claims 9-17, wherein the substrate comprises a product wafer.
 - 19. A method according to any of claims 9-18, wherein the at least one diffractive structure is either positioned within the chip or in the scribe-lane.
 - 20. An apparatus configured to perform a method according to any of claims 1-19, wherein the apparatus comprises:

an illumination system for providing a beam of radiation;

- a support structure for supporting a patterning structure configured to impart the beam with a pattern in its cross-section;
- a substrate table for holding the substrate; and
- a projection system for projecting the patterned beam onto a target portion of the substrate.

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Title of the Development

Method to separate dose and focus based on scatterometry spectra

State of the Art

Phase shift focus monitor can determine defocus (but not dose)

Line-end-shortening can be used to monitor defocus. The sign of defocus, however, cannot be retrieved.

Problems of the Art

It is very difficult to discriminate between dose and focus when measuring CD variations. In general, special or multiple features are needed in combination with special or time consuming metrology (see above). Especially, determining the sign of defocus is difficult.

Short Description of a method according to an embodiment of the invention

Calculates dose and focus using scatterometry spectra and principal component analysis (PCA)

- 1. Calibration of a focus dose model using scatterometry spectra from an experimental FEM
- 2. Predict dose and focus using scatterometry spectra as input for this model.

PCA is used to extract the relevant information from the spectra and thereby reducing noise in experimental data. By compacting the data, better calibration models can be build.

Repro (3σ): ΔF=30nm, ΔE=0.9% (based on comparing results obtained with H and V-iso lines exposures on an AT:1100 lithographic machine)

Potential Merits of the Development

Direct determination of scanner correctables instead of using the intermediate step of CD. No RCWA* needed:

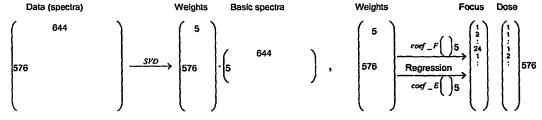
- at least some embodiments of the invention may be practiced without forehand knowledge of optical properties of materials
- 2. fast and simple prediction algorithm
- Works, in principle, on all structures: 1D (standard for scatterometry), 2D, but also directly on-product
- * Rigorous Coupled Wave Analysis: complex algorithm to calculate spectra based on a theoretical resist grating and process stack. To extract grating parameters from the spectra, it may be desirable or necessary to solve the inverse problem.

Further Description of the Development

Principal Component Analysis (PCA) can be applied to obtain the basic spectra describing the complete series of spectra. These basic spectra are called the principal components. In one example analysis as shown below, a scatterometry spectrum that consists of 644 points could be reduced to 5 basic spectra. These 5 basic spectra are linear combinations of the 644 points. The basic spectra are used to calibrate a model with dose and focus.

This model can than be used to predict dose and focus, based on new spectra.

Calibration



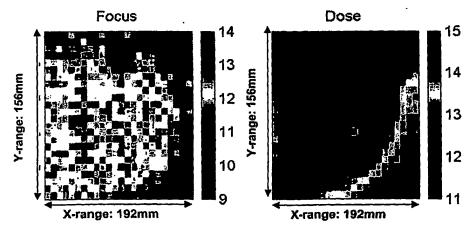
Verification and use

Data (spectra) (Basic spectra)^{$$f$$} Weights Focus & Dose
$$\begin{pmatrix}
5 \\
644
\end{pmatrix} = \begin{pmatrix}
5 \\
\hline
644
\end{pmatrix} = \begin{pmatrix}
5
\end{pmatrix} \xrightarrow{coef_F()5} F = \dots \\
\hline
coef_E()5
\end{pmatrix}$$

Examples of experimental results

On AT:1100 (M3031) 576 fields are exposed at Best Focus and Best Energy, covering an area of 192 x 156 mm² on the wafer. Small fields, in the order of mm's, are used. For one position per field the scatterometer records a spectrum, which is used as input for the model.

The figure gives the result for the determined focus and dose across the wafer. Each step in focus is 20nm and each step in dose is 1.25%. In the dose plot a typical processing fingerprint (and one flyer) is seen.



NSV V

Focus measurements with scatterometry

Hans van der Laan December 2003 <file name>
<version 00>
<author>

/ Slide 1

Outline

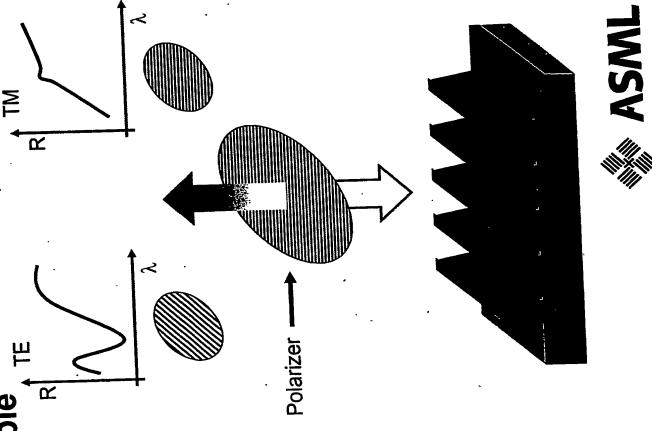
- Introduction
- Experimental
- Principle
- Create model based on calibration step
- Results
- Correlation to other focus techniques
- Use of Scatterometry Focus Technique
- . Conclusions



Scatterometry principle

Measure reflectance as a function of

- Wavelength
- Polarizer orientation: TE or TM
- Scatterometry types
- Reflectometer
 perpendicular incidence
 polarized & non-polarized
- Ellipsometer
 Oblique incidence



Introduction

- Two ways-of-working with scatterometry
- Use optical constants of materials + complex calculations (inverse Maxwell) to derive CD-values from spectra (standard)
 - Direct translation of spectra into Focus and Dose values, using an experimental calibration step (proposed here)
 - Advantage: outputs are the scanner adjustables
- Concept
- Spectra contains info on resist profile (focus dependent)
 - No special mask necessary as for PSFM / LVT tests
- Accuracy will depend on Scatterometry and resist type



Closed loop focus control Closed loop litho cell with scatteron MSW W Dose map per route (e.g. hotplate) multiple Unicom settings, config Unicom blades ffwd correction of mask errors Interface with FAB-APC system dose/field, dosicom/field and SEM presentation SPIE 2004 DoseMapper part of ISD-roadmap (Scat.) Track | Analyser Scanner DoseMapper + Enhanced Exp in Rel. 8.8.6 DoseMapper + Enhanced Exp in Rel. 3.4 APC upgrade (only new OTAS rel.) CD Mapper feasibility at IMEC / Slide 5 AWSUM upgrade, Rel 3.5 CD Mapper_1, Rel 3.5 CD Mapper_2, Rel >3.5 HV-Optimizer, Rel 3.5? MaskMapper, Rel 3.5? Focus Mapper requirements DoseMapper JDP AMD

Experimental

AT:850, M8868, NA=0.8, 0=0.85/0.55

110nm isolated line (pitch 1:6, binary mask)

Wafers from MEMC, deliberately made unflat

. Re-coated and re-exposed several times for the different tests

Scatterometer KT SpectraCD

• Oblique incidence, MAM = 4s/pt (Move - Acquired - Measure)

Calibration on 13x9 mini FEM (flat wafer)

• Focus: $-300 \Rightarrow 60$ nm, Dose: $26 \Rightarrow 32$ mJ/cm²

Scatterometry read-out on ELM-Scat FWCDU wafers

Focus tests to correlate with:

Levelling Verification Test (LVT)

, Wafer Map, MA



Principle

Calibration with FEM

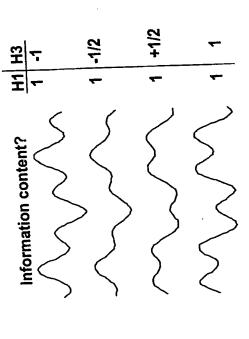
Focus & Dose determination on product wafer

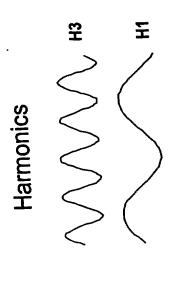
Spectrum from product wafer Energy = E2 Best match for: Focus = F2 Intensity match Best Spectra from FEM Energy 罚 딦 Focus <u> 2</u> F4

MSW WI

de 7

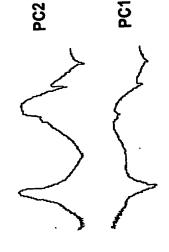
Principle of PCR



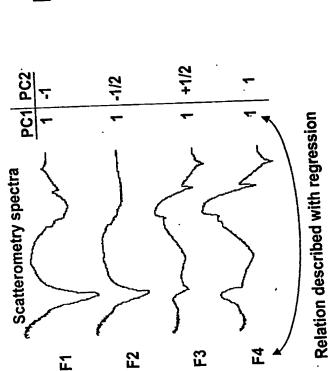




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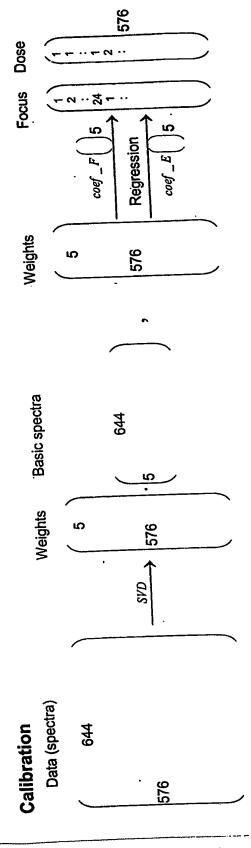






ASML Microsoft Excel

Principle Component Regression [RCar]

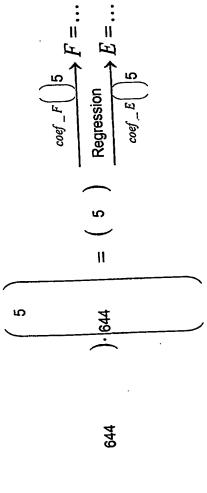


Focus & Dose

(Basic spectra)^T Weights

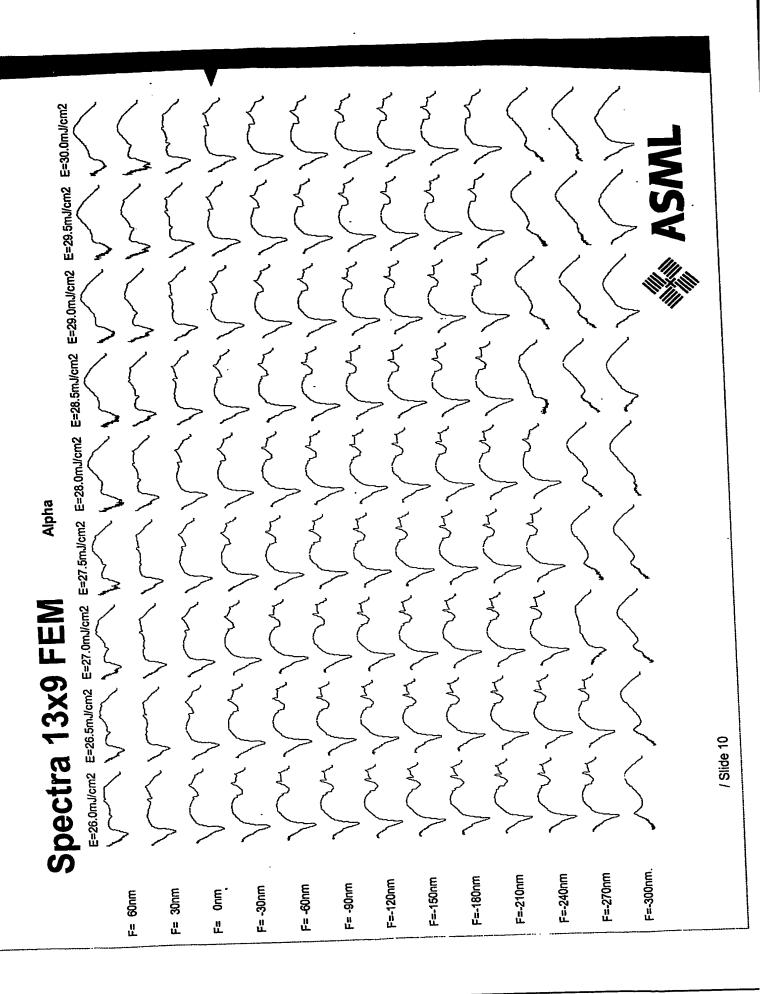
Verification and use

Data (spectra)

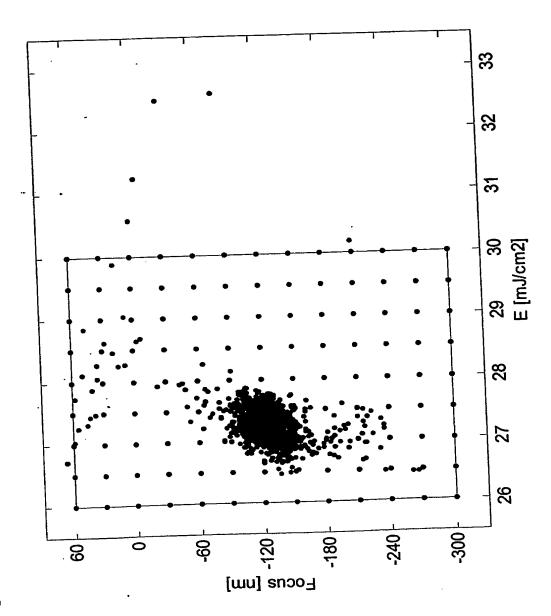




/ Slide 9

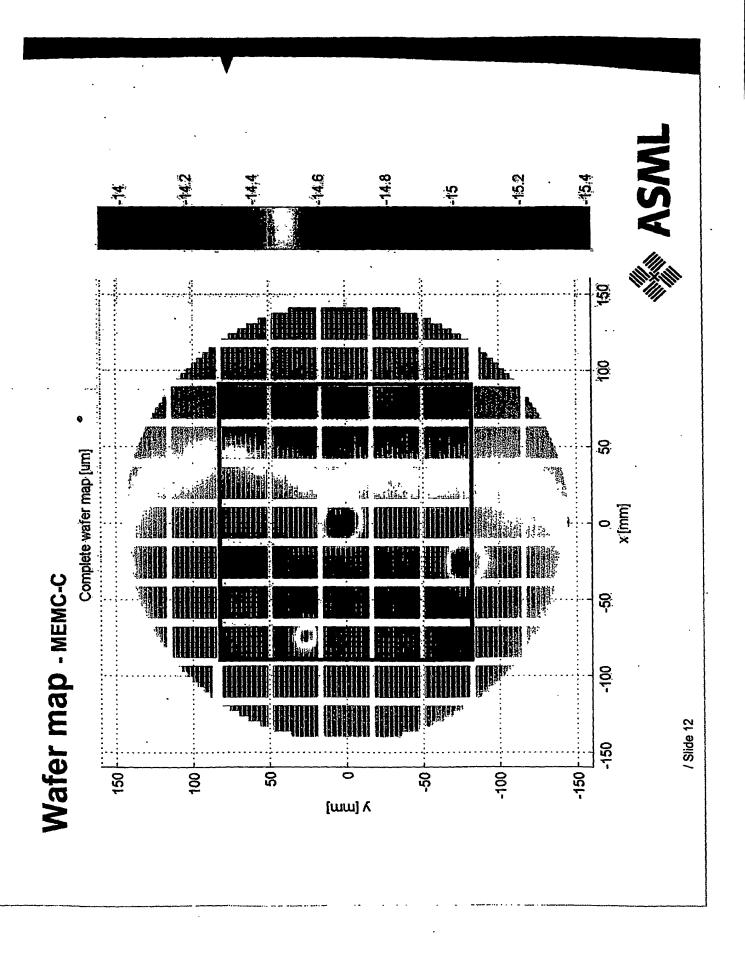


Apply model to Full Wafer spectra

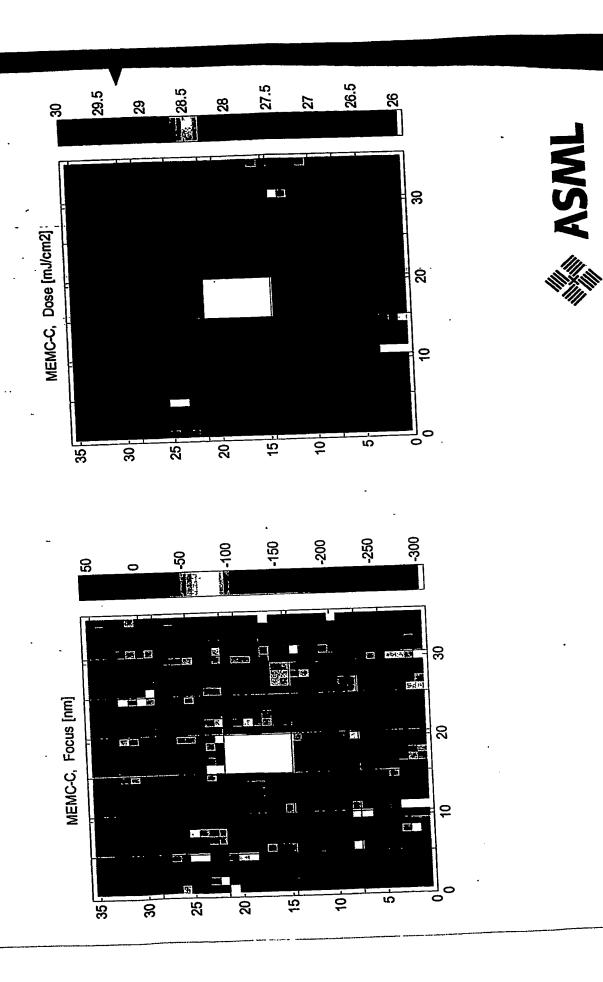


MSW WSWI

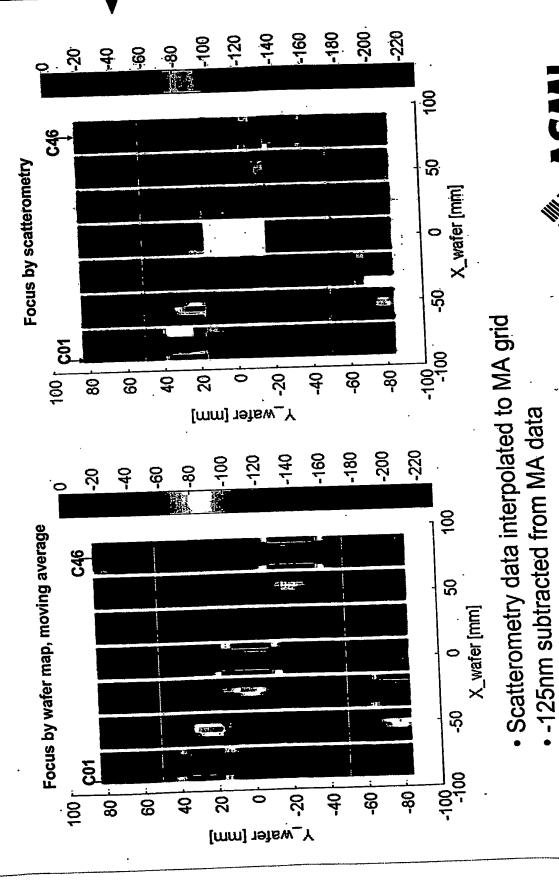
/ Slide 11



Focus & Dose measurements with scatterometry



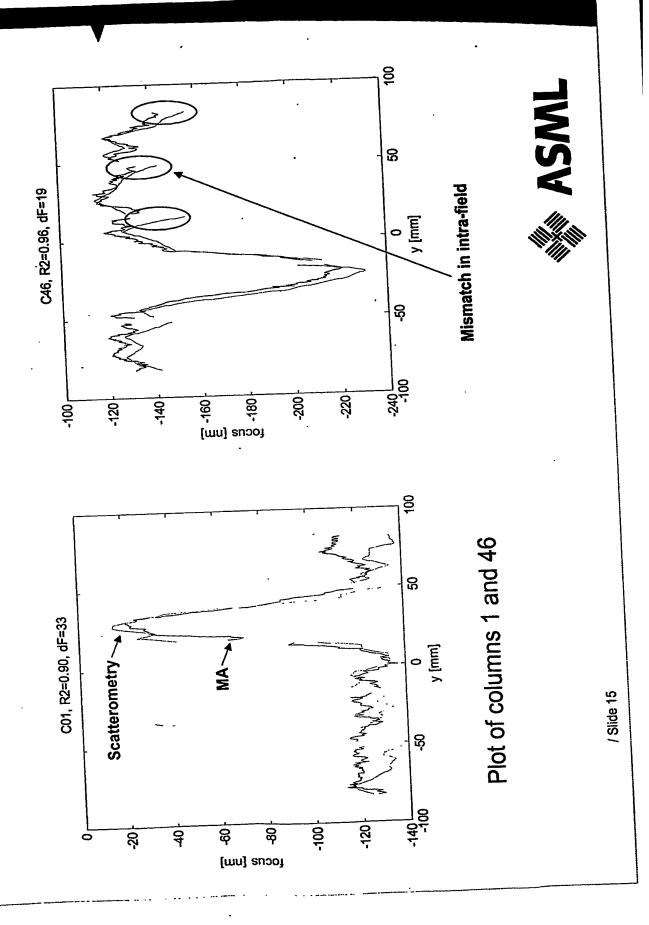
Focus by Wafer map (MA) vs. scatterometry



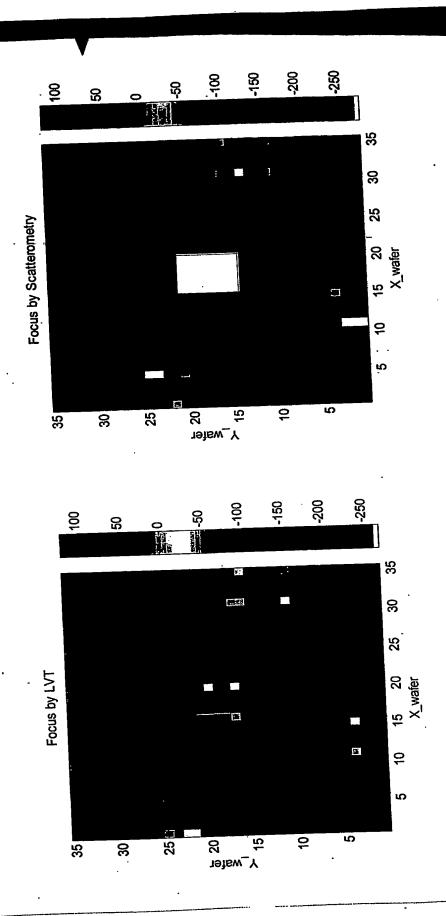


/ Slide 14

Focus by MA vs. scatterometry

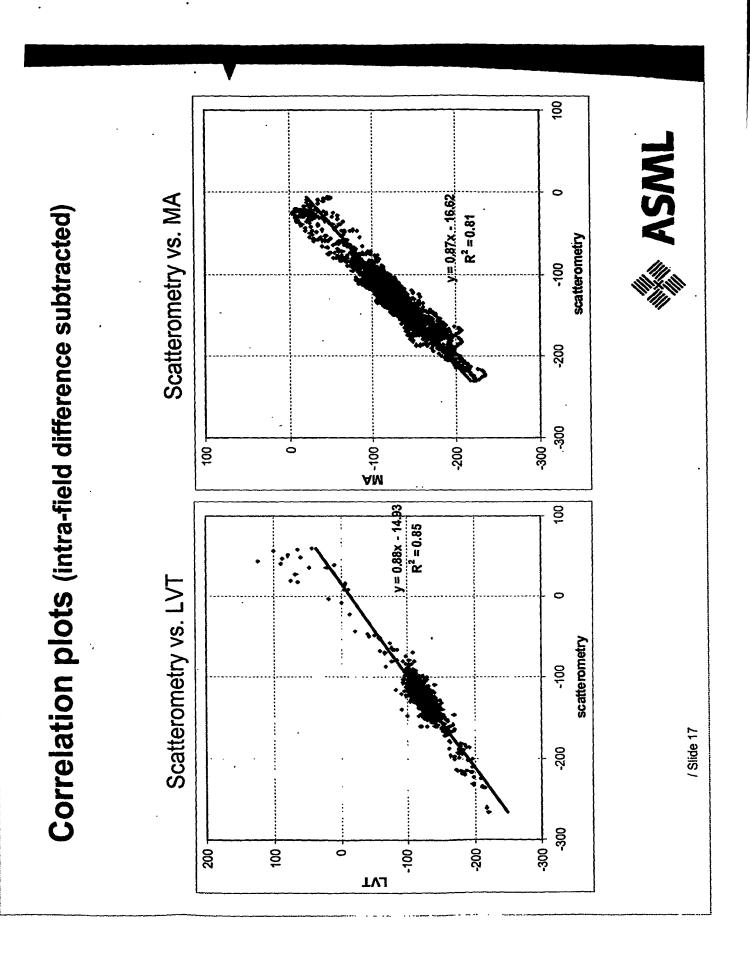


Focus by LVT vs. scatterometry









Accuracy

	lation					
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		Z Z				25
		900	χ ₂	dF [nm 3σ]	slope	۲
	dF [nm 30]	adole			88.0	0.85
	30	0.87	0.81	98	9	<u>}</u>
MEMC C. a	07	5	•		70.0	0.76
	i.	0 03	0.77	30	0.0) ; ;
3	C7	0.00	•		70.0	0.81
•	č	200	0.71	3/	5.0	· •
MEMC_D, a	<u></u>	-	1	. 36	0.81	0.74
	27	06.0	0.73	20		
<u>o</u> .	17			36	0.85	0.79
	27	0.88	0.75	000		
Average						

Intra-field difference subtracted

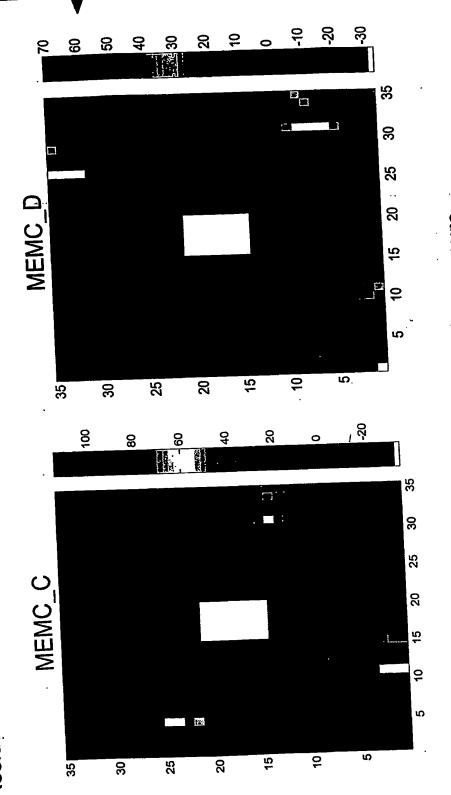
- Accuracy (3σ) < 25nm
- Based on correlation results
- Example: Ry accuracy < $0.2\mu m$ (3 σ), using 75 measurements



/ Slide 18

Use of Scatterometry Focus Technique

Residual of the LVT/Scatterometry correlation



Focus offset differences between the two exposures are seen LVT and scatterometry are based on a separate exposure



Slide 19

Conclusions

- Good correlation with LVT and Wafer Map, MA-data
 - Accuracy of Focus by Scatterometry <25nm (3a)
- Scatterometry is flexible since it works
- with all mask types
- with all illumination settings
- (as long as calibration done on the same substrate) on test wafers, on scribe-lane and within chip
 - with test structures / chip structures



Possible further experiments

Use of the Scatterometry Focus Technique

Adjust focus knobs for imaging structure and resist

Compare with FOCAL

. Does CD-Uniformity improve?

Repeat experiment on production like structure

E.g. Brick Wall, Contact Holes, real product reticle??

On top of product

. Calibration: Expose a FEM, rework wafer after read-out

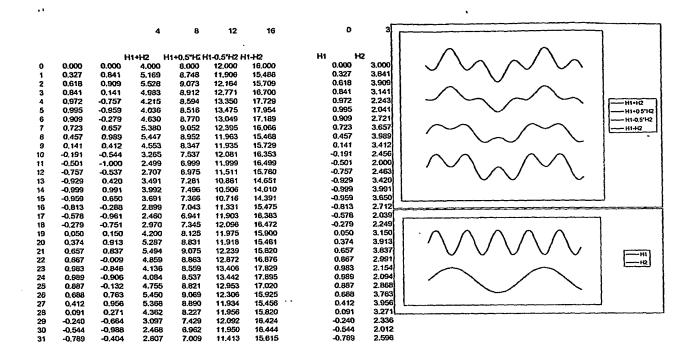
Use on the to-be-measured-wafers (Full Wafer Coverage)



Possible further experiments

- New investigations
- . Use MA data for calibration step
- Determine absolute BF directly from Focus Meander
- Investigate dependency on resist and scatterometry type
 - Investigate dependency on process variation other than Focus/Dose
 - . Try to decrease dependency





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5	PC2		PC2			PC1-0.5°F					· \	$\langle \ \ \rangle$	١.	<u> </u>	T.	=				=		
- 9-	-0.0282	0.0550	0.1118	0.0275	0.1916	0.3698	0.5339				- \/				Ц							===
- 8		0.0582				0.3723					~ 4				H			,	^			H
10	-0.0287	0.0555 0.0586	0.1113	0.0268	0.1912	0.3599	0.5342						\					/	1	_√		A
12	-0.0280	0.0588	0.1120	0.0307	0.1945		0.5368				\ \		~		坩						W -	Ħ
13	-0.0268 -0.0278	0.0575	0.1134	0.0309							ď		_		14			_	~		Y	Н
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15	-0.0290	0.0597	0.1110	0.0253	0.1952	0.3742	0,5386				`	\sim	h	_	Ц			,	V	•	~ ~	Ħ
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22	-0,0295	0.0517	0.1105	0.0221	0.1869	0.3884	0.5312				~ .	~ <i>/</i>	h	\	H	=	=					
23 24	-0.0325	0.0662	0.1075		0.1900	0,3724	0.5387							\checkmark	貫			=			=	===
25 26	-0.0293	0.0587	0.1107	0.0273				<u> </u>										$=\pm$				
27 28		0.0542		0.0232			0.5351 0.5344															
29	+0.0300	0.0554	0.1094	0.0249	0.1901	0.3707	0,5360					==	==									
30 31	0.0290	0.0554	0.110	0.0255	0.1904	0.3701	0,5350															
32 33	-0.0320	0.0524	0.1080	0.0204				<u> </u>							-	=						
34 35	-0.0344	0.0549	0.1056	0.0200	0.1878	0.3721	0.5393			==								-	=			
36	-0.0317	0,0582	0.108	0.0245	0.1903	0.3720	0.5379					=	==						==			
37	-0.0313	0.0536	0,108	7 0.0200	0,1857	0.3670	0.5327														==	
39 40	-0.032	0.0568	0,107	7 0.0245 2 0.0247														\longrightarrow				=
41	-0.0328	0.0506	0.107	0.0178	0.1842	0.3670	0.6334			==				==		-	==					
43	-0.029	2 0,0500	0.110	0.0217	0.1863	0.3655	0.5301			==			= 1							===		
44		0.0513	0.108	0.019																		
48	-0.032	0.0540 7 0.0511	0,107	0.0216									 -1									
49	-0.030	0.0500	0,109	0.0196	0,1849	0.3651	0.5301															=
50	0.029	0.0494	0.110	0.019	0.1648	0.3643	0.5292															
51 52		2 0.0516			0.165	5 0.3856	0.5310	1													==	
53 54	-0.030 -0.025	0.0628	0.109	9 0.022 6 0.019		0.3679																
55	-0,027	3 0.0483	0,112	7 0.021	0.184	7 0.3620	0.5256															
57	-0.033	3 0.0487 3 0.0511	0,108	7 0,017	0.184	4 D.3677	0.5343	3										==				
56 59		6 0.0471 3 0.0523																				
60 61	-0.028	2 0.0504	0.111	8 0.022	2 0.186	3 0.3645																
62	-0.029	4 0.0493	0.110	6 0.019	0.184	5 D.3640	0.5287															
63 64	-0.032	4 0.0452 6 0.0518	0.107	4 0.019	1 0.185	4 0.368	0.534	1														
85		0.0487							<u> </u>													
67 68	0.028	6 0.0501 3 0.0480	0,111	4 0.021																		
69	-0.028	6 0.0493	0.111	5 0.020	7 0.185	0 0.363	0.527															
7 9	-0.027	5 0.0478 7 0.048	0.112	3 0.020	7 0.184	8 0.362	3 0.526															
품		0 0.0474	0.112	9 0.019	1 0.182	7 0.350	7 0.523	3														
光		9 D.0474 8 0.047							 												<u> </u>	
76	0.023	5 0.042 8 0.047	0.116	5 0.019	0.180	8 0.354																
遥	0.026	4 0.048	3 0.113	6 0.021	9 0.185	0.361	5 0.524		-													
79 80	-0.022	0.044 5 0.045	5 0.117	5 0.023	0.164	2 0.356	8 0.518	0	<u> </u>													
흹		5 0.046	0.117 2 0.116	9 0.020																		
禀	0.024		2 0.116	0,023	2 0.165	2 0.350	2 0.521	2	-					 				 				
- 25	-0.022	0 0,042	3 0.116	0.020	3 0,181	3 0.353	3 0.514	3	1=					 					F	F.—		
	-0.022	6 0.046	9 0.117	2 0.024	2 0.185	8 0.358	3 0.519	7														
8	-0.019	2 0.044	2 0.120	0.023	0.182																	
哥	-0.019	8 0.043	3) 0.120	0.023		0.353	1 0.512			-					-	 	<u> </u>	<u> </u>		<u> </u>	<u> </u>	\vdash
92		5 0.044 71 0.040	0.111	6 0.024	0,184	3 0.354	9 0.515	1		<u> </u>	F			<u> </u>	F	<u> </u>		F==				二
뿗	-0.019	M 0.043	4 0.121	0.024	0,163	0.353	1 0.512	8	1													
88	-0.019	0 0 042	1 0.12	0.02	3 0.18	32 0.355			1						<u> </u>							
3	-0.017	2 0.043 6 0.043	0.12	28 0.025	8 0.184	0.351	6 . 0.510	2	-													
99	-0.013	33 0.041	8 0.12	0.02	0.186	0.348	0.505	0	1-							 		F	=	F		口口
100	-0.013	57 0.040 57 0.039	0.12	33 0.020	0.183	30 0.348	7 0.503	6	#==							!==		<u> </u>				
膃	-0.01	4 0.039 1 0.041	0.12	58 0.020					 	<u> </u>				<u> </u>	<u>t </u>		<u> </u>	<u> </u>		<u></u>	<u> </u>	
104	-0.01	17 0.038 32 0.039	8 0.12	0.02	2 0.18	30 0.344	7 0.500	6		-	μ		==		 						F	
10 10	-0.01	38 0.041	2 0.12	0.02	74 0.18	43 0.348	0.506	ō		<u> </u>		<u> </u>			1==	 			F	<u> </u>	1	
10	-0.01	29 0.039 18 0.039	0.12	82 0.02	76 0.18	35 0.345	0.501	1	1					1	<u> </u>			<u> </u>				
10	-0.01	15 0,039 08 0,039	0.12	26 0.02	0.18	38 0.345	0.501	1		1	 					·	<u></u>		<u> </u>	<u> </u>		
111	-0.01	18 0.038	7 0.12	84 0.02	71 0.18	29 0.344	15 0.500	3	1	-	 	F		F=	F			1=	F			
11	-0.00	87 0.032 80 0.038	0.13						1						J	1	<u> </u>					

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114	-0.0068	0.0378	C 0 1312	0.0291	0.1834	03422			<u>'-</u> -	 				-~-								
115	-0.0000	0.0386	0.1310	0.0295	0.1840	0.3430	0.4976															
115		0.0362				0.3390				}												
116	-0.0052	0.0358	0.1338	0.0278																		
119	-0.0060	0.0358	0.1340	0.0298																		
120 121		0.0353					0.4906															
122	-0.0059	0.0350	0.1341	0.0290																		
123	-0.0049	0.0343	0.1351	0.0293																		
124 125		0.0369																				
126	-0.0044	0.0352	0.1358	0.0306	0.1830										!							
127		0.0354									<u>-</u>											}
126 129	-0.0023	0.0342	0.1377	0.0302			0.4859															
130	-0.0009	0.0329	0.1391	0.0319	0.1824	0.3334	0.4838															
131		0.0340										 										
133	-0.0018	0.0351	0.1382	0.033																		ļ
134	-0.0013	0.0334	0.1387	0.0320											l							
135 138	-0.0011	0.0335	0.1385	0.032				 -			<u> </u>		1									
137	-0.0012	0.0334	0.1388	0.032	0.1828	0.3340													 		ļ	
138		0.0329										<u> </u>							-			
140	-0.0007	0.0315	0.1383	0.032																		F
141	0,0010	0.0314	0,1410	0.0324											 					 		
143	0,0020	0.0336	0.1420	0.035					 	 												
144	0,0008	0.0347	0.1400	0.035	0.1850	0.334	0.4841											<u> </u>				+
145		0.0321							<u> </u>			 			 			 	 	 	 	
145		0.0333							 													
148	0,0045	0.0313	0.144	0.035	0.1830	0.329	0.4769								<u> </u>					ļ		
148		0.0318							 	 	 	 			 			<u> </u>	<u> </u>			
150 151	0.0065	0.0317	0.148	0.038																		\vdash
152	0,0072	0.0314	0.147	0.038	0.185	0.327	0.474							<u>-</u>	 	·		 	 	 	 	+
153	0.0069	0.0330	0.146	0.039						 	 	 	 									
155	0.0088	0.0314	0.148	0.040	2 0.185	0.327	0.472	3										<u> </u>			 	+
150	0.0090	0.0320							 	 	 	}	 	 	 	 -	[t	 		 	
157 158	0.0117	0.0312		7 0.042	9 . 0.187				<u> </u>													1
159	0.0125	0.0315	0.152	0.043						\sqsubseteq					 			 	 -	 	 	┼──
160 161	0.0133	0.0312	0.153	2 0.044 3 0.044					 	 		 	 	 	┼~~							
182		0.0316		0.046	6 0.189	2 0.324	3 0.486	9										<u> </u>			ļ	
163		0.0306		0.047					 	 	 	 	├	 	 	├ ──	 	 	├──		 	
164 165		0.0301	0.158	8 0.047 4 0.048	0 0.185 5 0.189					 	 											1
188	0.018	2 0.0300	0.150	2 0.049	2 0.189	3 0.320	4 0.460	9						-					 	 	ļ	
167		0.0297							 -		├	├	 	 	 	 		 	 	 	1	
168 169		0.028		1 0.05	9 0,190																	7
170	0.025	1 0.0280	0.165	1 0.053						T	ļ	ļ			 	 	├	 	 	 	 	┼
171		0.0276 3 0.0262	0,165	4 0.053 3 0.055	8 0.190				}	 	 		 	 	 	 	 			t		_
173	0.028	4 0.0263	0.168	4 0.054	0.190	6 0.312	2 0.448	ol											-		ļ. <u>'</u>	
174	0.030	8 0.0271								├ ──	+	+	 	 	 	 	├ -		├	 	 	
175		8 0.0250 1 0.0250	0.171	0.05					 	-	 	1	1									二
177	0.034	5 0.0254	0.174	5 0.064	0.192	6 0,300	0.440									Ţ				 	 	┼
177		4 0.025 1 0.025	0,174	4 0.05					 	 	+		}	}	 	 		 	+	1		
179 180		7 0.024	0.17	7 0.08																		
181	0.039	6 0.022	0.17	6 0.06	23 0.192					Ţ	1				-	╂		 	╂	 	 	
182 183		2 0.022 4 0.021	0.181	2 0.05					┼──		+	+	┼	 	+	 	1	 	 	1		
164	0.043	3 0.021	0.18	0.00	0,193	2 0.29	9 0.428	2	1				1		1						7	
185		0.020	0.18	0.06						┼				 			├	 	 -	┪───	 	
187		8 0.018	0.18	0.06							1				上二				1			
188	0.048	7 0.018	0.18	7 0.08	72 0.190		0.419	9				Ţ	Ţ <u> </u>	ļ	1			 -				
189		0.018	0.18	0.08					 	+	+	1	+	+	+	1	<u> </u>	1	<u> </u>			士
190 191		7 0.015	0.19	7 0.08	75 0.19	6 0.26	0.414	1								1					\leftarrow	\perp
192	0.053		0.19	0.06	0.19	5 0.28			+	+	 -	+	 	1		 	 	+	 	+	+	+
199		4 0.014							1	1								1				
199	0.058	6 0.013	0.19	56 0.07	0.19	18 0.28	53 0.40	0	-	4	4	4	4	+	4	 	 		 	+	 	+-
190 197				74 0.06 33 0.07				18	+	+	+	+	+			+	 		1	1		
198	0.060	0.012	0,20	0.07	20 0.19	0.28	20 0.40	20	1	1			T	 	+	\leftarrow			+	<u> </u>		+
125		7 0.010	0.20	07 · 0.07	12 0.19 06 0.18	0.28			4		+	+	+	+	+			+		1	+	
20X 201	0.061	9 0.000	0.20	18 0.05	84 0.18	75 0.27			1										1		Ţ	
203	0.083	8 0.007	5 0.20	38 0.07	12 0.18	3 0.27	58 0.39	37			4	+	+	+			+		 		+	
38	0.083	0.007	21_0.20	39 0.07					+	+	+		<u> </u>	1			1					
200	0.066	0.005	0.20	92 0.07	11 0.18	81 0.27	19 0.38	38	1	1	1			1					 			4
200	0.086	0.004	0 0.20	51 0.07 75 0.07						+			+	+			+	+	 		1	
20 20	0.087	75 0.003 73 0.001	21 0.20	73 0.00						1	土							=				工二
200	0.057	0.000	2 0.20	79 0.00	80 0.18	41 0.20	62 0.38	23	-	-	4	4	+	4		4	+	+	1			+-
219	0.08	0.000 22 -0.000	7 0.20	86 0.08 62 0.08							+	+	+	+	+	+	+		 	-		
3	0.069	-0.002	2 0.20	99 0.00		27 0.26							1				1				=	
213	0.08	90 -0.002	8 0.20	0.00	73 0.18	23 0.26	24 0.37	74					+	4		+=		-		+	+	
21	0.070	03 -0.004									+		+	+		+	+			 		土
21 21		13 -0.000																				
21	0.07	23 -0.006	2 0.21	23 0.00		99 0.25	76 0.37	15	-	4	4		+	4	-	+	+			+		+
21 21	0.07	10 -0.007 13 -0.007	0.21	10 0.00			69 0.37 70 0.37		1	+	+	+		+		1	1		-	1		
23	0.07	00 -0.006	0 021	06 0.00	0.17	55 0.25	47 0.36	93		-	1	7				1	Ţ					
	0.07	15 -0.006	0.21	15 0.00	18 0.17				-			+								+	 	1
123		06 -0.010	7 0.21				30 0.36				\pm			土二				_	上二			
22	0.07									1	-	1					1 ~ ~	1				!
22 22 22 22	0.07	90 -0.012	21 0.20	00 00		28 0.2																
22 22	0.07 0.08	97 -0.012	2 0.20	97 0.0	577 0.17 573 0.17 568 0.17	24 0.25	27 0.36	79	1	1-		-	1-	1	+	1		-	-		=	\equiv

Α											М	N	0	Р	0	R	S	<u> </u>	U		-1
	6 (c D	E	F	G	Н			I K									+-	 -	┼─	-
0.0686	-0.0143 O.	2088 0.05 2079 0.05					\pm			ļ	L		 					1			7
0.0679	-0.0149 0. -0.0158 0.			78 0.251	3 0.36	82	Ţ		 	 							├	+	┪		_
0.0652	-0.0166 Q	2062 <u>0.04</u>					+				ļ	<u> </u>	 				1			\top	7
0,0845	-0.0157 0	2045 0.04							 	 			—				Ε		-		-1
0.0841	-0.0164 O		54 0.18	40 0.251	3 0.37					1						 	-		1		
0.0510	1-0.01721_0	2010) U.U.											├	1	 						
0.059	-0.0187 0	1994 0.04 1984 0.04	07 0.16		0.37	737		Ι			 					ļ	 				
0 037	0.0123	1779 0.00	56 0.15									<u> </u>	ļ	 		 	+				
0.036	3 -0.0110 0	1763 0.00					—							- 	 						
0 034	8 -0.0101 0	.1748 0.0 .1732 0.0						Ţ <u> </u>	-	-		┪	1				ļ				
0,033	2 -0.0089 0 3 -0.0081 0		232 0.15	575 0.27	831 0.4	106								<u> </u>	 	+	+	+			_
0.029	9 -0.0084	1699 0.0				159					-			+	 	-					
0.028	2 -0.0058 _0),16821 0.0	224 0.15 226 0.15										1	+				_ļ			
0.027	0 -0.0043 (590 0.28	371 0.4	210	_				-i			-	-	-			-i		
0.024	41-0.0020	0.1844		601 0.28		238						-			-						
0 02	3 -0.0016	0.1623 0.0		596 0.25 504 0.25		285						+	-i -								
0.02	0 0.0011		212 0,1	612 0.29	0.4	1311								Ţ <u></u>	-			-+-	_		_
0.01	7 0.0022	0.1587) O.C		615 0.21		4358						<u> </u>									
0,01	72 0.0030			616 0.21		4377				_			_								
0.01	55 0.0039 55 0.0054			1631 0.2	978 0.	4398		_		+-						-	+-				
0.01	40 0.0063	0.1540 <u> 0.4</u>		1633 0.2		4423		┥──									-				_
0,01	33 0.0073	0.1533 0.1	0206 0.1			4459							 -	+					_		
	22 0.0061 10 0.0092		0203 0.1	1647 <u>0.3</u>	037 0	4482	\Box														_
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0.00	92 9.0106	0.1492 0.				4529				\bot				1-							_
	0.0113 076 0.0129		0205 0.	1667 0.3	3091 0	4553					\pm	ユニ							-+-		_
0.0	0.0132	0.1466 0	0196 0.	1665 0.3		4585	-														_
0.0	0.0140	0.1458 0	0198 0			4597								-	=					$-\vdash$	
0.0	052 0.0150 044 0.0155			1677 0.3	3133 0	.4511						士							 		_
0.0	035 0.0161	0.1435	0.0196	1879 0.	3144	0.4826											_ _		=		_
0.0	030 0.0165	D.1430				0.4853			\Box			-		-							
0.0	022 0.0175 014 0.0178		0.0192	1685 0	3171	0.4884	\Box				_						-+-	_+-	-		_
00	007 0.0184	0.1407	0.0191			0.4877	$-\!\!+\!\!-$								-						
0.0	0.0188	0.1404				0.4597												_		<u></u>	
	0003 0.0194 0012 0.0196			0.1690 0.	3202	0.4706															
7	1015 0 0203	0.1385	0.0188] (0.4718															
5 -0.0	0.0206	0.1376				0.4740							-+-								
B -0.	0030 0.0210 0032 0.0219			0.1703 0	.3235	0.4750		-				$\neg \vdash$	$\overline{\cdot}$			_					_
-0	0.0219	0.1357	0.0177			0.4762			-+				_								
0-0	00441 0.022	0.1356				0.4778					-										
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	0000 0 023	0.13401	0.0175	0.1705	3265	0.4794															\equiv
43 -0	0064 0.023	7 0.1336			0.3269	0.4809															
-41	0071 0.023 0074 0.024	5) 0.132VI			0.3280	0.4818					-+						_				
26 -0	.0077 0.024	7 0.1323	0.0169		0.3285	0.4824															
87	00021 0.024	91 0.13181			0.3290 0.3295	0.4831											•				
	0064 0.025 .0068 0.025	3 0.1312		0.1700	0.3297	0.4841									-	-					
001 -0	00031 0.025	8 0.1307	0.0165		0.3304	0.4851															
91 -	0.0097 0.025	2 0.1303	0.0165		0.3311	0.4881															
93 4	0.0100 0.020	7 0.1298	0.0165	0.1716	0.3318	0.4870								-				-+			_
94 4	0.0109 0.026	7 0.1291	0.0158		0.3321	0.4876															
96 4	0.0112 0.02	9 0.1288	0.0158		0.3327	0.4883															
	0.0112 0.02	4 0.1282	0.0158	D.1715	0.3333	0.4892		 -													
298	0.0120 0.02	76 0.1280	0.0158		0.3336	0.4895										-					
2001	00123 0.02	77 0.1277	0.0154		0.3344	0.4907		=										+			
201	0.0128 0.02 0.0128 0.02	62 0.1272	0.0153	0.1718	0.3346	0.4910	-+							\Box	_	-+					
777	0.0132 0.02	84 0.1268	0.0152		0.3350	0.4918									-+						
202	0.0134 0.02	26 0.1266 L	0.0151	0.1718	0.3354	0.4922															$\overline{}$
305	0.0136 0.02	87) 0.12011	0.0147	0.1717	0.3358	0.4926	_ 							$=$ \mp							
308	0.0142 0.02	91 0.1258	0.0149		0.3362	0.4933						 -									-
207	00144 00	92 0.1258 93 0.1251	0.0148	0.1720	0.3367	0.4942												 1			-
300	.0.0149 0.0	293 <u>0.1251</u>	0,0144	0.1718	0.3367	0.4942		 -						\Box							
310	O 0153 Q 0	295 0.1247	0.0142]		0.3371	0.4948							+								1
311	0.0154 0.0	295 0.1246	0.0141		0,3375	0.4953															+
343	-0.01601 0.0	297 0.1243 296 0.1240	0.0138	0.1718	0.3378	0,4958	+								-+						二
714	COMMITTED OF	2001 (1.1239)	0.01301		0,3380		+								+						+
7146	0.01871 0.0	300 0.1233 302 0.1233	0.01331		0.3385	0.4969															+
247	-0 0470 Q.C	3011 0.1230	0.0131	0.1715	0.3386	0.4972		 +									 +				I
244	AM72 DC	ran21 0.1228	0.0130									F			_		==1			 	+
319	A 0175 00	304 0,1225 304 0,1222	0.0129		0.3393	0.4983								$= \pm$							士
320 321	A 01791 D.0	3041 0.1221	U.UIZU	0,1715	0.3394	0.4983							==			+					T
322	-0 0183 O.	305 0.1217	0.0122		0,3396								 -							 	-
323	-0.0185 0.0	0305 0.1215 0305 0.1214	0.0121		0.3398	0.4991													 	├─	+
褮	O IRRINA.	03051 0.1212	0.0110	0.1710	0.3390	0.4993										+			<u> </u>		工
325 326	-0.0192 0	0308 0.1208 0308 0.1208	0,0118	0,1712	0.3404									\longrightarrow							4
327	-0.0195 0.	0308 0.1208	0.0111																1	 	+
328	-0.01981 0	0306 0,1204 0307 0,1200			0.3407	0.5007										==		 -	+		+
333	-0.0201 0	0309 0.119	0.0100	0.1708	0.3410		<u>_</u>												1		工
鐡	_0.02041.0	CC3UBI 0.1194	31 0.010	0.1700						\sqsubseteq						1			ullet	 	+
	0.0207 0	0307 0.119	ու ט.ט⊶	6 0.1703		3 0.5018						—— 							+	1	+
332		0306 0.118	0.000	4 0.1700	0.341	2 0.5018	 		 					\Box				 			ユ
332 333				2 <u> 0.1700</u>															Τ	<u> </u>	-1-
332 333 334	-0 02151 C	WU/ U.110										-,									
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	^	B	C	D	E	F 0.7477	G	н			_ K		M	N.		-Р	-	-8	- \$	7	2	
340 -0 341 -0	0220	0.0308	0.1174	0.0000																		
342 -0.	0233	0.0306	0.1187	0.0073	0.1690	0.3422	0.5039															
		0.0308		0.0071	0,1688																	<u> </u>
344 -0 345 -0	0239	0.0305	0.1161	0.0087																	 	
				0.0084																		
	10244	0.0307	0.1156	0,0062																		
348 -0	0247	0.0307	0.1153	0.0068	0.1681																ļ	
				0 0057																		
		0.0305		0.0052																		
	0258	0.0305	0.1145	0.0050																		
353 -0	0260	0.0304	0.1140	0.0044															<u> </u>	 		
354 -0	1.0281	0 0304	0,1139					 	 -										 	 		
		0.0302		0.0038																-	 	i
357 -0	0.0269	0.0303	0,1131	0.0034	0.1669																	
358 -0	0.0270	0.0302	0.1130	0.0031									L					ļ	 	ļ	 	
359 -0 360 -0	0273	0.0302	0,1127	0.0029				 	 										 	 	 	
		0.0301						 		-				 					<u> </u>			
362 -0	0.0280	0.0301	0.1120	0,0021	0,1661	0.3441																
		0.0301								ļ	<u> </u>		ļ	 				 -	 	 		
		0.0300							 					 	 					 -		1
366 -0	0.0288	0.0299	0.1112	0.0012																		T
367 -0	0.0290	0.0299	0,1110	0.0010	0.1654	0.3444	0,508														 	ļ
		0.0296							}		 	 	<u> </u>		 		 		 	 	 	
369 -0	0.0297	0.0298	0.1107	0.0005	0,1852		0.509		 		 		l					1				
371 -0	0.0298	0.0297	0,1102	-0.0001	0,1648	0,3446	0.509	il												J	J	-
372 -0	0.0299	0.0297	0.1101	-0.0002	0.1647	0,3440	0.509	j		-								ļ	}	 	 	
373 -0 374 -0	0.0303	0.0298	0.1097	-0.0007							 		 	 		 		 	1	 	1	
				-0.0010					T	 	 	l			1		<u> </u>					
376 -0	0.0307	0.0298	0,1093	-0.0010	0.1543	0.3450	0.510	4												ļ	1	1
377 -0	0.0310	0.0298	0.1090	-0.0014							 	 			 	 	 	 	 	 	 	
		0.0294							 	 	 	 	 	 	 		1	1	1	1	1	1
350 -0	0.0315	0.0294	0.1065	-0.0021	0,1836	0.345	0.510										<u> </u>					
381 -	0.0319	0.0293	0,1061	-0.0025	0.1634	0.345	0,511	2		1			,	!					 	 	 	1
		0.0292		-0.0026						 	}	 		 		 -	 	 	 -	 	 	
383 -0 384 -0	0.0323	0.0294	0.1072	-0.0028	0.1533					1	 		1	1	 	 _ _ _ 	<u> </u>	 		1		
385 4	0.0326	0.0293	0.1074	-0.0033	0,1630	0.345	0,511	3														
386 -0	0.0328	0.0293	0.1072	-0.0035	0,1521	0.345	0,512		<u> </u>			ļ	ļ	4	 			 	1	}		
387 -4	0.0330	0.0294	0.1070	-0.0036	0.162	0.345			 	 	 		 	 		 	 	 	1	 	+	1
				-0.0040						1			<u> </u>	<u> </u>								
390 -0	0.03361	0.0294	0.1054	-0.0042	0,1626	0.346	0.513	0									<u> </u>				1	-
				-0.0046						 	<u> </u>	 	├ ──	 	 	}			 		 	┼
		0.0294		-0.004					 	 		 		} -	} -	 	 	 		┼──	 	
		0.0293								 	-			1	1							
395 -	0.0348	0.0295	0.105	-0.005	0,152	2 0,348												<u> </u>				ļ
		0.0294								 	 	├ ──	 	 -	├ ──	├	 	 	 			
	0.0352	0.0295	0.104						 -	+	 	 	 	┿	 	 -	 	1	 	 	 	
399			0.104	-0.005																		
400 -	0.0358	0.0298	0.104	-0.006	0,161								1		Ţ					 	 	
401	0.0359	0.0296	0.104	-0.008							 			↓ -	 	 	 	┼	 	} -	}	
				5 -0.006					 	 	+	 	 	+		 	 		 	1	<u> </u>	
				3 -0.008																		1
	0.0370	0.0300	0.103	-0.007	0.161								 	├ ──	 	 	 		├ ──		+	
				-0.007 -0.007					 -		+	 	┼			 	 		 	+	 	
408	0.0377	0.0302	0.102	3 -0.007	0.181				+	 	1	1	1									
409	0.0370	0.0303	0.102	1 -0.007	5 0.181	4 0.349	3 0,518	2				T		T	1				-			
				0 -0.007					╀──	 -	├ ──		 	+	 			+			+	
412	0.0381	0.0305	0.101	9 -0.007	5 0.181				1	1	1	1	1	1	1			1		上二		
413	0.0381	0.0305	0.101	-0.007	0,161	5 0.349	6 0.516	6											Ţ			1
414	0.0380	0.0307	0.102	0.007	3 0.161				+					 				1	-{	+		+
415	0.0378	0.0307	0.102	2 -0.007 3 -0.007	2 0.161 1 0.161				+	+	+	 	+	 	+	+	1	 	1	1		
317	0.0375	0.0307	0.102	5 -0.008	8 0.181		5 0.518	2								I				1		
418 -	0.0372	0.0307	0.102	8 -0.008	6 0.162					+	+	+	_				1					+
	0.0371	0.0307	0.102	9 -0.006	4 0.162 4 0.162				+	 	+	+	+	+	+	1	1	 	 	1		
421 -	0.0367	0.0306	0.103	3 -0.006	1 0.162	2 0.348	9 0.517	3														
472 -	0.0385	0.0300	0.103	5 -0.005 9 -0.005	0.162	3 0.348	8 0.51			-		-	4	+	4	 		+	+	 	 -	+
	0.0361	0.0306	0.103	9 -0.005 2 -0.005	8) 0.162 3 0.162	5 0.348			 		 	+	 			+	+	- 		+	 	1
425	0.0355	0.0305	0.104	4 -0.006	1 0.162				1	1												
426	0.0353	0.0306	0.104	7 -0.004	8 0.162	8 0.345	0.51	8	\perp			1					+=	-				
				0 -0.004		0.34			+		-	+	+		+	+	+		+		 	
429	0.0347	0.0304	0.105	3 -0.004	2 0.163	0.347			1	1	1	1	1	1	1	1		1	1	士二	工二	
430 -	0.0344	0.0304	0.105	6 -0.004	1 0,183	2 0.347	8 0,514	8			—	1	1			1						
431 -	-0.0342	0.0306	0.106	8 -0.003	6 0.163							1-	+	+	+		+	-			-{	
- ASS -	0.0341	0.0304	0.105	0.003 1 -0.003	6 0.163 3 0.163			<u> </u>	+	+	 			 	+	+	+	 			+	
433	-0.0338	0.0300	0.100	2 -0.003	0.163				1		1		1			1						
435	0.0337	0.0306	0,106	3 -0.002	9 0,164	0.34	8 0.51	5			-						+					-
435	9.0334	0.0306	0.100	8 -0.002	5 0.164	0.347	6 0.51				+			+	-}					+		+
				8 -0.002						+	+	 -		+	+	1	1	 		+	1	1
439	-0.0329	0.0312	0.107	1 -0.001	7 0.164					1		1										
440	-0.0326	0.0313	0.107	4 -0.001	4 0.165	0 0.34	6 0.51	10			-	1				-	+				4	
				5 -0.001	1 0.165							ļ	+	4		+					 -	
		0.0318		7 -0.000						 	+	+		+	1	1	 -	+	+		1	
44	-0.0319	0.031	0.100	0.000	0.162		77 0.51	36														
445	-0.0318	0.0320	0.100	2 0.000	2 0.160	31 0.34	78 0.51		-		-	+			+	4		$\overline{}$			4	+
		0.035								1	1	+	+			+	- {	+				
		0.032							+	1	+	1		1						1		
		0.032					0.51															
450	-0.0000	0.032	0,100	0.001	7 0.16	71 0.34	0.51					4	+	4	4		+					
451	0.0300	0.032	0.10	0.002							1	+		+		+						+
452				~ v.v.	J. 10	77 0.34	V.01	- 11											_1			

	Ā		С		E	F	G	Н		J	к	L	М	Ň	0	P	٩	R	S	Ţ	U	V
453 454	-0.0301	0.0332	0.1097	0.0031	0.1681	0.3483	0.5133 0.5133														==	
455 450	-0.0298	0.0335	0.1102		0.1888	0.3484	0.5133															
457 458	-0.0295	0.0338	0.1104	0.0043	0.1690	0.3486					==											
459 450	-0.0291	0.0341	0.1100	0.0047 0.0050	0.1693		0.5133 0.5133															
451 452			0.1111																			
483			0.1115																			
465 468	-0.0281	0.0349	0.1119	0.0068																		
467 468	-0.0278	0.0352	0.1122	0.0074	0.1713	0.3491	0.5130															
469 470	-0.0275	0.0356	0.1125	0.0061	0.1719	0.3493	0.5131															
471 472	-0.0269	0.0359		0.0090	0.1724	0.3493																
474	-0.0265	0.0362	0,1135		0.1729	0.3495	0.5128															
475 476	-0,0260	0.0366	0,1140	0.0108	0.1736	0.3495	0.5125															
476	-0.0258	0.0362	0.1144	0.0112	0.1740	0.3498	0.5124															
479	-0.0250	0.0370	0.1150	0.0120	0.1745	0.3495	0.5120															
487	-0.0247	7 0.0374		0.0127	0.1751	0.3497	0.5120							-								
483	-0.024	1 0.037	0.1150	0.0138	0.1757	0.3498	0.5116															
485 485	-0.0235	5 0.038	0.1165	0,0145	0.1783	0.3498	0.5116								<u> </u>				F			二
487 488	-0.0225	9 0.038	0.1166	0.0154	0.1769	0.3495		1					<u> </u>	<u> </u>						F		二二
489	902	5 0.038	0.1175		0.177	0.3500	0.5112						<u> </u>		 				<u> </u>		<u> </u>	口二
490	-0.021	8 0.039	0.1181	0.0187	0.1780	0.3500	0.510						-	F==	 							\Box
492	-0.021	4 0.039	0,1184 2 0,1186 4 0,1190	0.0179		0.3499	0.510		 					<u> </u>					ļ	 	F	
494 495	-0.020	7 0.039	0.1193 0.1193 7 0.1197	0.0190	0.178	0.3490	0.510	3			 			==					 		ļ	1
497	-0.020	1 0.039	9 0,1199	0.0196	0.179	0.3499	0.510															二
495	-0.019	5 0.040	0 0.1202 2 0.1206	0.0200	0.180	0.3500	0.509	/	===				 	<u> </u>	 				-		 	二
500 501	-0.018	8 0.040	0.1200 6 0.1212	0,0218	0,181	0,3490	0.500	3						<u> </u>					!	<u> </u>		=
583 583	-0.018	2 0.040	7 0,1215 6 0,1216	0.022	0.181		0,508			<u> </u>			<u> </u>	==	<u> </u>			<u> </u>	1==			=
504 505	-0,017	4 0.041	0 0.1222 2 0.1226	0.023	0.182	0.3499	0.500	3					! ===	 	 	<u> </u>		1				=
506 507	-0.018	7 0.041	3 0.1230 5 0.123	0.0248	0.183	0,349	0.506	2			<u> </u>				<u> </u>				 	<u> </u>		二二
508 509	-0.015	0.041	8 0.1230 8 0.1240	0.025	0.183	8 0.349	0.507	8					<u> </u>						-		 	二
510 511	-0.015	0.042	0.124	0.028	0.184	4 0.349	0.507	•	_	\vdash		<u> </u>								 	==	1
512 513	-0.014	15 0.042	3 0.125 4 0.125	0.027	0.186	1 0,349	7 0.508	0			===		<u> </u>	1	 			<u> </u>	1=			1
514 515	-0.013	37 0.042	8 0.125 7 0.126	0.029	0.165	0.349	0.508	4											 			
518 517	-0.012	29 0.043	0 0,126	0.030	1 0.166	5 0.349	0.505	0					$\pm =$	 								
518 519	-0.012	22 0.043	2 0.127 3 0.127	0,031	1 0,187	2 0.349	4 0.505	6							$\pm =$				1==	 	 	
520 521	-0.011 -0.011	14 0.043	5 0.128 6 0.128	8 0,032	2 0.187	9 0.349	0.508	a	 	<u> </u>		<u>لــــــــٰ</u>			 	<u> </u>			 	<u> </u>		1==1
522 523		09 0.043 06 0.043	7 0.129 8 0.129	1 0.032 4 0.033			1 0.504	4	_		<u> </u>	<u> </u>	$\pm =$	<u> </u>		\perp	\vdash	 				1
524 525	-0.010	96 0.044	0.129	2 0,034		2 0.349	0.503	9		$\vdash =$	$\pm =$	<u> </u>	 	 	 						\pm	
526 527	-0.000	90 0.044	0.130	0.035		0.348	9 0.503	4	\pm		 		$oxed{oxed}$			<u> </u>						
526 529	-0.000	62 0.04	0.131 6 0.131	6 0,036		4 0.348	7 0,500		_		 	<u> </u>	$\pm =$	 			<u> </u>	\vdash			 	
530 531	-0.00	78 0.04 75 0.04	17 0.132 18 0.132	2 0.036 5 0.037	9 0.190 3 0.191	0.348	6 0.50	4					$\pm \equiv$			<u> </u>	<u> </u>					
532 533	-0.00 -0.00	71 0.044 68 0.044	19 0.132 19 0.133	9 0.037 2 0.038	0.191	4 0.348 5 0.348	0.501	8				1			 	<u> </u>	<u> </u>			==		
534 535	-0.000	64 D.044 60 0.044	51 0.133 52 0.134	6 0.038 0 0.039	7 0.191 2 0.192	0 0.348 2 0.345	3 0.50° 2 0.50°	2							 				1	<u> </u>	<u> </u>	$\pm = \pm$
536 537	-0.00	68 0.04 63 0.04	3 0.134 54 0.134	4 0.039 7 0.040	0.192	Ø Q.348	0,500	77	1	-			$\pm =$	<u> </u>			<u> </u>	 	1		 	1
28	-0.00	49 0.04	6 0.135 6 0.135	1 0.040	0.193	2 0.347	9 0.50	12	$\pm \equiv$				1	1	<u> </u>	 	1_			 	 	
540 541	-0.00	42 0.04 38 0.04	6 0.135 6 0.135 57 0.136	8 0.041 2 0.041	4 0.19 9 0.19	5 0.347 8 0.347	7 0.49 6 0.49	6	1				$\pm \equiv$	+==	<u> </u>				$\pm \equiv$		1	+==
	-0.00	35 0.04	58 0.136 58 0.136	5 0.042 9 0.042	3 0.194 5 0.194	0.347 3 0.347	5 0.49 4 0.49	9		$\pm \equiv$				<u> </u>	+==			\pm	+-	1	 	
54 54	-0.00	27 0.04	59 0.137 50 0.137	3 0.043	3 0.19	6 0.347 8 0.347	2 0.49	X6	士三	$\pm \equiv$		 	_	1	+==	$\pm =$	 					
54 54	-0.00	18 0.04	0.138 0.138	2 0.044	2 0.19	0.347	0 0,49			$oxed{\Box}$			$\pm \equiv$	1					1=	+-	1	1
	-0.00	111 0.04	0.138 0.139	0.045	1 0.19	6 0,346	7 0.49	71	$\pm =$						1	1		$oxed{oxed}$		$\pm \equiv$	1	
88	-0.00	03 0.04	54 0.136 54 0.146	7 0.048	0.19	3 0.34	0.49	37		 	7	+	-	$\pm \equiv$	$\pm \equiv$	$oxed{oxed}$	\equiv	E				
靐	0.00	05 0.04	85 0.140 85 0.141	6 0.047	0.19	8 0.346	3 0.49		+	-	-	\mathbf{F}	\equiv	\pm	$\pm \equiv$	$oxed{oxed}$		\pm		\pm		
醬	0.00	114 0.04	67 Q 141	4 0.046	0.19	74 0.340	SO 0.49	53	+	7-	+	+	 	\pm	\pm	$\pm =$	=			-	1	
55	0.00	23 0.04	88 0.142	3 0.049	0.19	0.34	58 0.49	44	 	1-	 	-	+-	1-	+	-		F	-			£
E E	0.00	32 0.04	58 0.142 59 0.143 89 0.143	2 0.060	0.19	0.34	53 0.49	37	1-	+	-	1	-	-	-	+=	-	-	 	-	\pm	$\pm \equiv$
8	0.00	42 0.04	89 0.144	2 0.051	0.19	0.34	68 0.49	27	1-	1-	#==	1==	#	-	-	 	-		-	+-	_	1=
8	0.00	62 0.04	70 0.144 71 0.145	2 0.05	22 0.19	98 0.34	(5 0.49	19	+	+=	#	-	+	1=	+	+-	+	1-	+	-	+-	7=
<u>\$</u>	1 0.00	611 0 04	71 0.145 71 0.146	11 0.05	33 0.20	02 0.34	61 0.49	10	-	#==	#==	‡==	1-	1=	-		+	+-	#		1]==
56	0.00	671 0.04	72 0.14	0.05	0.20	05 0.34	0,49	w)					·									

													M			PI		R	s	Ţ	U U	- V 1
506	0.0072	0.0472	0.1472	0.0543	0.2007	0.3436	G 0,4900	н		- 4	К			N	-0		_ 0				-	
587	0.0076	0.0472	0.1478	0.0548	0.2010	0.3434	0.4898															
568 569			0.1485																			
570	0,0090	0.0471	0.1490	0.0581	0.2015	0.3426																
푌			0.1495			0.3424					 -											
573	0,0102	0.0470	0.1502	0 0573	0.2021	0,3419	0.4568															
574 575	0.0108	0.0470	0.1508	0.0576				 	<u> </u>													
576	0.0113	0.0489	0.1513	0.0583	0.2026	0.3413	0.4856															
577 578	0.0117	0.0482	0.1517 0.1520	0.0588			0.4851	<u> </u>			-									 		
579	0,0124	0.0487	0.1524	0.0591	0.2029	0.3405	0.4844															
580 581			0.1520						ļ	 			ļ		 				<u> </u>			
582	0.0131	0.048	0.1531	0.0598	0.2031	0.3400	0.4834															
583 584			0.1534								 			 				 		 	 	
585	0.0138	0.0483	0,153	0.0601	0.2032		0.4828															
586 587			0.1539												 			 -		}		
588	0.0145	0.048	0 1545	0.0607				 		 	 											
589 590	0.0145	0.046	0.1546	0.0606								ļ		 				 	 	 	 	
591			D.1560																			
592	0.0153	0.048	0.1553	0.0813			0.4800									<u> </u>		 	 		 	
593 594			0.1556						t					 								
595	0.0181	0.048	0.1581	0.0621	0.204	0.3370	0.4790			-		ļ			 			 	}		 	
598 597			0.1564						<u> </u>													
598	0.0170	0.045	0.1570	0.062	0.204	0.337	0.478			 	<u> </u>		=					}	 		1	├ -
599 600	0.0245	0.043	0.1645	0.087		0.3311					 		<u> </u>									
601	0.0253	0.042	0.165	0.068	0.205	0.330	0.467								<u> </u>					 	-	
502 603			0.1856 4 0.1866						 	 		 	├	 	+		 	 				
604	0.0262	0.042	2 0.166	0.038	0.205	0.329	0.458)												F	1	1
606 608	0.0260	0.042	0.168	0.068					 		 		 	 -		 	 	 	 		1	
507	0.0270	0.041	8 0.1670	0.068	0.205	0.328	0.464	3					1		-				\vdash	 		1
608 609			5 0,187 3 0,187							 	-		 	 	 		 	 	 	1		
610	0.0278	0.041	2 0.167	0.058	7 0.205	0.327	0.483	3							<u> </u>							1
811 812	0.0278	0.041	0 0.167	0.068	8 0.204	0.327			 		├ ──	ļ	 -	 	 	 		 	 	 	 	1
613	0.0281	0.040	0,168	1 0.068																		
514	0,0283	0.040	7 0.168	0.059		0.326										 	 		 			
615 616			6 0.188 4 0.168						<u> </u>	t												
617	0.0284	0.040	4 0.168	8 0.069		8 0.325	0.461			T-				Ţ							├ ──	
618 619			3 0,169 2 0,169						┼──		+	 		+	 	├──		 	·		1	
620	0.029	7 0.040	1 0.169	7 0,069	6 0.206	0 0,325	3 0.460	4												F		
823	0.0300	0.040	0 0.170 6 0.170	0 0.070					}	┼	┼	 	 -	 	+	 	 -	 	 	}	1	1
623	0.030	0.039	7 0.170	6 0.070	2 0.204	9 0.324	4 0.450	1										Ţ <u> </u>		ļ	-	
624			5 0.170 1 0.170			8 0.324 5 0.323			 	 			┼			 	 	 	 	1	 	
626	0.030	4 0.032	8 0,170	4 0,069	2 0.204	0 0,323	6 0.458	4							1			1				
627 626			3 0.169 9 0.169						 		+	 	 	┼		├──	 	 -			 	
629	0.026	7 0.037	8 0.158	7 0.066	3 0.201	9 0,323	3 0.458	9													Ţ	
630 631	0.028	8 0.037	5 0,188 6 0,168	6 0,068					┼──	 		 	 	+		1	 	 	+	 	 	
632	0.029	0.03	0.169	6 0.067	7 0.200	8 0.323	1 0.450	2														
633 634			6 0.171 71 0.172							+		 		┼	+	 	 	+	┼~~~	 	-	
635	0.035	2 0.040	0.175	2 0.075	2 0.20	6 0.322	4 0.454	8	1									-			T	
636			8 0.177 6 0.180								┽	┼	+	+	-	 	 			+		+
637 638	0.042	8 0.043	4 0,182	5 0.065	2 0.21	0.321	0 0.449	6			1	1		1								
640			0 0.185 0.187		0.21					+	+	4		+		 	 	+	+	 	+	
641	0.049	0.04	0.185	0.097	9 0.21	4 0.310	4 0.44	9	1		1	J	1		T			 	1			
643	0.050		(Z 0.190						+	+		 	+	+	+	+	+	1		1		1
644	0.053	1 0.04	5 0.193	0.097	7 0.22	1 0.318	0.44	4	1	1	#==	1	1===	1	1		Ţ	1-	1	1	-	
645 646	0.054	1 0.04	6 0.194 7 0.195	1 0.09	7 0.22 6 0.22					-		 		+		+	+	+	+	+	+	1
647	0.058	0.04	(8) 0.190	0.100	0.22	28 0.316	8 0.43	38				1	#==	1			1		1			
648	0.056		18 0.190						1	1	-		+					+	+		+	-
549 550	0.057	8 0.04	68 0.197 48 0.197	6 0,10	25 0.22	0.310	0.43					1		1			1	1	1	1		
85	0.068	0 004	18 0.19	0 0.10					+	+	+			+			+					
85 85	0.066	4 0.04	8 0.196 17 0.196	2 0.10 4 0.10	31 0.22	39 0.31	58 0.43	34										1	1		1	
05	0.058	5 0.04	47 0.194 47 0.194	5 0.10					+	+	 	+	+	+	+	+	+			+	+	
555 555	0.058	5 0.04	17 0.190	55 0.10	32 0.22	39 0.31	54 0.43	12	1	1						1	1			1	1-	
65	0,058	0.04	45 0.190	0.10	30 0.22		54 0.43	32	-	1			+	+ =		+	1	+			-{	
854 654		0.04	45 0.194 45 0.194	0.10 33 0.10					-		1				+	1			1			
064	0.058	2 0.04	4 0.19	2 0.10	27 0.22	35 0,31	53 0.43	52	=		1	-	-	+=	1	4	+					
66		U 0.04	43 0.194 43 0.194	0.10 3 0.10			52 0.43	50	1	+		1	土	 	1	1	土	1		上二		1
66	0.068	3 0.04	12 0.19	3 0.10	25 0.22	33 0.31	51 0.43	50					+=	 		T		1	+		-	
80			40 0.19							+				+	-	┼	+			+		
56	0.058	34 0.04	39 0.19	0.10	23 0.22	31 0.31	47 0.43	55		1	\bot	1	1			1		1_	1-		1	
66	0.068	6 0.04	38 0.10	5 0.10 5 0.10		30 0.31 29 0.31			 	1		 -	 -		4	+	+	+	+			_
55 55	0.052	0.04	35 0.19	0,10	21 0.22	28 0.31	42 0.43	49										=	\pm		1-	
07	0.058	17 0.04	34 0.19	67 0.10									+	+=		+	+	+				
57 57		10 0.04	33 0.19 31 0.19	85 0.10 89 0.10				-	+	1		1				1						
57	0.050	0.04	30 0.19	20 0.10	20 0.22		35 0.43	39		\top			+	 	 			+	+	+		
87	0.056	3 0.04	25 0.19	92 0.10 93 0.10					+		1		1	+		 	1		$\pm -$	上		
67	0.050	25 0.04	25 0.19	95 0.10	20 0.22	23 0.31	28 0.43	30	1			1==	4==	7=		1	7	T		—	1	+
왔	0.05	0.04	24 0.19	95 0.10	18 0.22	21 0.31 20 0.31	26 0.43 23 0.43	25			+-	 	1			-}	 	+	1			
1,07	9.050	SVI 0.04	cz 0.19		V-64			**!														

		$\overline{\Lambda}$	8	С	D	E	F.	G	н	1	3	к		м	N	0	Ρ	0	R	5	Ţ	U	V
650			0.0420		0.1017	0.2218	0.3121																
681	1 (205001	0.0416	0.1999	0.1015	0.2215	0.3116	0.4317															
88	1-8	0.0600	0.0414	0.2000	0,1014	0.2214		0.43141															
584	1	0.0601	0.0410	0.2001	0.1012	0.2211	0.3110	0.4300															
188		0.0502	0.0408	0.2002	0,1010			0.4308															
687		0.0603	0.0404	0.2003	0.1006	0.2205	0.3102	D.4301															
688 886			0.0402		0,1005			0.4299															
690			0.0397	0.2003	0.1001			0.4294															
691			0.0395			0.2197 0.2195		0,4292															
893	1	0.0603	0.0391	0.2003	0.0994			0.4285															
694 698			0.0388			0.2189	0.3067	0.4286												<u> </u>			
690		0.0501	0.0388	0.2001	0.0985			0.4284															
697			0.0351																	ļ			
696			0.0379					0.4279															
70		0.0597	0.0374	D, 1997	0,0971	0,2172																	
70			0.03/1					0.4276					<u> </u>							<u> </u>			
700	1	0.0591	0.0355	0,1991	0,0058	0.2181	0.3070	0.4275															
70	-	0.0585	0.0359	0.1985	0.0951						·	[
70		0.0582	0.0358	0.1962	0.0938	0.2147	0.3065	0.4274															
70	-	0.0579	0.0354	0.1979	0.0934			0,4274		 	ļ		 	<u> </u>		<u> </u>							
70	2	0.0575	0.0349	0,1975	0.0924	0.2136																	
7			0.0348 0.0342								 					1				 			
71	3	0.0564	0.0339	0,1984	0.0903	0.2121	0,3057	0.4275		<u> </u>			\vdash										
717	\mathbf{T}	0.0656	0.0338	0.1958	0,0889						\vdash	 	<u> </u>	<u> </u>	<u> </u>								
71	2	0.0652	0.0329	0.1952	0,0681	0.2106	0.3053	0.4277															
71			0.0326			0.2094	0.3052	0.4270		<u> </u>			 		 					<u> </u>		t==	
71	3 [0.0538	0.0319	0,1938	0,0857	0.2068	0,3060	0,4281			F==					\sqsubseteq					-		
71 72			0.0318						 		 	 	 		 	 	 	 	 -			 	
72	4	0.0522	0.0300	0.1922	0,0031	0.2070	0.3048	0.4287							F==							 	<u> </u>
光			0.0305									 		 -	 	 	 			1	 		f
72	<u> </u>	0.0508	0.0298	0.1905	0,0804	0.205	0.3045	0.4292															
175		0.0600	0.0294	0,1900	0.0794					 		 	 	 	 	├		 		 	 	 	
.72	7	0.0487	0.0267	0.1887	0.0774	0.2030	0.3043	0,4300															
72		0.0481	0.0283	0.1881	0.0763					├	 	 	 	 	 	 		 		 	 	 	
73	0	0.0467	0.0275	0.1567	0.0742	0.200	0,3041	0.4306															
끊			0.0271							 		 	 	 	 -	 	 -			 	 	 	├
73	3]	0.0448	0.0264	0.1848	0.0712	0.198	0,3040	0.4316															
深	4	0.0441	0.0260	0.184	0.0701					 	 	├	├	├		 -	 	 		 	 	 	
173	뷥_	0.0425	0.0255 0.0251	0.182	5 0.0878																		
12			0.0247							 	 	 	 	 	├ ──	├ ──	 	 	 	 			
73	9	0.0403	0.0243	0.1600	3 0.0542	0.194	0.3037	0.4336															
74			0.0234							 		<u> </u>			 	 	 		 -	-	 	 	├ -
174			0.0226																				
74	3	0,0369	0.0221	0.176	0.0590					ļ		 							├	₩		-	1
74			0.0210							<u> </u>													
巫	81	0.0340	0.0207	0.174	0.0547							ļ			ļ	I				 			
74	#-	0.0336	0.0204	0.172	7 0.0520					t		1	<u> </u>		1	1	<u> </u>					1	
.74	9	0.0318	0.0198	0.171	8 0.0514						ļ						ļ			 	╂		
75		0.0310	0.0191	0.170	0.0601						 						1						
75	2.	0.0289	0.0161	0.168	9 0.0470													ļ		-	 		
7	4	0.0278	0.0175	0.105	8 0.0454 8 0.0436					 	t	<u> </u>	 			1							
76	6]	0.0260	0.0186	0.158	0.042														<u> </u>	}		F	
7	7.1	0.0241	0.0162	0.164	1 0.0390			0,441	31											1			
75	8	0.0229	0.0151	0.162	9 0.038	0.176	5 0.3037	0.442		 _	-	1		\leftarrow	 	+	1		 	1	 	\vdash	
	न -	0.0209	0.0145	0.160	0.0350	0.174	8 0.3037	0.443	2						1								1
76	<u> 1</u>	0.0201	0.0137	0.160	1 0.033	0.173	8 0.3037	0.443	1			1				T				T_	-		
79	3 7	0.0177	0.0125	0.157	7 0.030		8 0.3037 4 0.3037					<u> </u>			\perp		<u> </u>	<u> </u>					
7	4	0.0163	0.0116	0.156	3 0.028	0.170	0.3037	0.445				1	 		T	1							F
75	러	0.0149	0.0114	0.154	9 0.026		0.3037			<u>t </u>	1			<u> </u>		1			\bot	上		上	1
7.75	7	0.0141	0.0106	0,154	1 0.024	0.187	8 0.3032	0,446		7==	-	-			ļ		}			-	-	 	-
75			0.0103				7 0.3038			 	1	1-			 	+	+	1	1	 		 	
77	0	0.0101	0.0000	0.150	1 0.019	0.163	9 0.3039	0.448		1		-		=		 	=		1	=			\vdash
77		0.0002	0.006	0.149	2 0.017 4 0.016					1	\pm	1			1	1	1				土	1	1
77	3	0.0072	0.0076	0.147	2 0.014	8 0.161	2 0.3040	0.450	3	Ţ <u> </u>	Γ	\leftarrow		 			=	ļ	1	F		\leftarrow	\leftarrow
Ţ,	5	0.0050	0.0083	0.145	0.012					+	1		+	1	1	+	 	1	1		1	1	1
7	6	0.0032	0.0056	0.143	2 0.008	9 0.157	3 0.3040	0.452	•			1					T-		=				\leftarrow
\mathbf{g}		0.0019	0.0050	0 141	9 0.008					-	 		1	+	 	+	+	+	1	+	 	+	
7	9	-0,0003	0.0039	0,139	7 0.003	6 0,153	7 0.3041	0.454	3	1	1	1	1				1	1		1	-	1	1
70	Q[_	-0.0016	0.003	0,135	0.001					-	+	1	1	+	+	 	+	+	 		+	 	
7		0.0041	0.0021	0.137	2 -0.000 9 -0.002	0.150					1		1	1								1	
7	3	-0.0054	0.0014	0.134	6 -0.004	0.142	7 0.304	0.458		-	1	+	+	+	4	4	4	1	+			+	+
B	쓁-	-0.0063	0.000	0.133	7 -0.006						1		1		1		上					\perp	
7	юI —	-0.0000	-0.0000	0.130	-0.010	7 0.144	3 0.304	0.450	1			1	-	+	 	Į							1
7	38	-0.0128	-0.0016	11 0.127	2] -0.015	3 0.141					1							$\pm -$	土				1
7	19	-0.0141	-0.0030	0.125	-0.017	1 0.139	0.304	0.461	0		=		-	1		=	-	\leftarrow	\vdash				-
H	읚	-0.0152	-0.003	0.124	8 -0.018	5 0.132 1 0.133				1	1	1		<u> </u>									1

ABC	1016	T F	1 6 1	нТ		7-1	к	- 1	M I	N I	0 1	PI	o T	R	s	7 7	U	V
792 -0.0156 -0.0043 0.124	41 -0.0199 0.3	379 0.3035	0.4813															
793 -0.0137 -0.0038 0.120 794 -0.0099 -0.0024 0.130	3 -0.0174 0.1	1394 0.3031 1427 0.3026																
795 -0.0048 -0.0003 0.139	2 -0.0061 0.1	1473 0.3021	0.4545															
796 0.0009 0.0021 0.140 797 0.0058 0.0043 0.140	0.0029 0.100	1525 0.3015 1571 0.3014	0.4512															
798 0 0087 0.0057 0.144	7 0.0145 0.	1501 0.3014	0.4470															
799 0.0097 0.0084 0.145 800 0.0095 0.0085 0.145	6 0.0161 0.	1612 0.3015 1613 0.3018																=
801 0.0003 0.0088 0.141	3 0.0158 0.	1612 0 3019	0.4473															
803 0.0088 0.00871 0.144	8 0.0155 0.	1612 0.3022 1611 0.3023																
804 0.0088 0.0087 0.144 805 0.0084 0.0087 0.144	0.0154 O. 0.0151 O.	1610 0.3024 1609 0.3025																
506 0,0060 0,0067 0.14																		
807 0 0077 0 0068 0 14 808 0 0073 0 0088 0 14	771 0.01431 0.	1505 0.3028 1602 0.3028																
809 0.0070 0.0065 0.14	70 0.0135 0.	1500 0.3030	0.4495															
810 0.0066 0.0064 0.14 811 0.0061 0.0063 0.14		1597 0.3031 1594 0.3033																
812 0.0056 0.0062 0.14	58 0.0118 0.	1590 0.303	0,4505															
813 0.0052 0.0061 0.14 814 0.0048 0.0060 0.14		1586 0.3035 1584 0.3036																
815 0.0045 0.0059 0.14	45 0.0104 0.	1581 0.303	0.4514															
816 0.0040 0.0058 0.14 817 0.0036 0.0057 0.14		1578 0.303 1574 0.303																
B18 G.0031 0.0055 0.14	31 0.0067 0.	1571 0.3031	0.4524															
819 0.0027 0.0054 0.14 820 0.0024 0.0053 0.14	27 0.0081 0. 24 0.0077 0.	1588 0.304 1585 0.304																
821 0.0019 0.0052 0.14 822 0.0014 0.0050 0.14		1561 0.304 1557 0.304																
523 0.0009 0.0049 Q.14	09 0.0058 0.	1553 0.304	0.4540															
824 0.000\$ 0.0048 0.14 825 0.0001 0.0048 0.14	05 0.0052 0. 01 0.0047 0.	1550 0.304 1547 0.304									ļ					 		
828 -0.0003 0.0045 0.13	97 0.0042 0	1543 0.304	0.4548															
827 -0.0007 0.0044 0.13 828 -0.0013 0.0042 0.13	93 0.0036 0. 87 0.0029 0.	1540 0.304 1538 0.304									<u> </u>		 	<u> </u>				
829 -0.0017 0.0040 0.13	83 0.0023 0	1532 0.304	0.4558															\Box
830 -0.0021 0.0039 0.13 831 -0.0025 0.0038 0.13	75 0.0013 0	1528 0.305 1525 0.306																
832 -0.0030 0.0036 0.13	70 0.0006 0.	1521 0.305	0.4567															
833 -0.0036 0.0034 0.13 834 -0.0041 0.0033 0.13 835 -0.0045 0.0032 0.13	59 -0.0008 0	.1516 0.305 .1513 0.305																
835 -0.0045 0.0032 0.13 636 -0.0049 0.0030 0.13	55 -0.0014 0	.1509 0.305 .1508 0.305													 	ļ	<u> </u>	
837 -0.0063 0.0029 0.13	47 -0.0024 0	1502 0.305	0,4582															
838 -0.0058 0.0027 0.13 839 -0.0063 0.0025 0.13	42 -0.0030 0	1498 0.305						 		 	 	 		 	 	 		
840 -0.0067 0.0024 0.13	33 -0.0043 0	1490 0.305	7 0.4590															
841 -0.0070 0.0022 0.13 842 -0.0074 0.0020 0.13	30 -0.0048 0 26 -0.0054 0	.1487 0.305 .1483 0.305					 		 	 	 	 				 		
843 -0.0080 0.0019 0.13	20 -0.0081 0	1479 0.305	0.4599															
844 -0.0086 0.0017 0.13 845 -0.0093 0.0015 0.13		1474 0.306				 	 	 	 -	 	 				l			
848 -0.0098 0.0014 0.13	02 -0.0084 0	1485 0.306	3 0.4612															==
847 -0.0103 0.0012 0.12 845 -0.0106 0.0011 0.12		1451 0.306					!	 		 								
849 -0.0109 0.0009 0.12	91 -0.0100 0	1454 0.306								ļ				 			ļ	
850 -0.0112 0.0007 0.12 851 -0.0117 0.0008 0.12		.1451 0.306 .1448 0.308																
852 -0.0121 0.0005 0.12 853 -0.0125 0.0003 0.13	79 -0.0118 0	1444 0.306						[ļ	 	 		 -	 	 	 	 	├ ── ┤
854 -0.0130 0.0002 0.12	270 -0.0128 0	1437 0.300	7 0.4832															
855 -0.0135 0.0000 0.1 856 -0.0140 -0.0001 0.1		.1433 0.306 .1429 0.306			 -		╂	 	 -	 	├	 	├	 	 	├		
857 -0.0145 -0.0003 0.1	255 -0.0148 0	1425 0.307	0 0.4843															\Box
858 -0.0150 -0.0005 0.13 859 -0.0152 -0.0006 0.13	248 -0.0159 0	.1421 0.307 L1418 0.307					├	 	 	 	 		 	 		 		
960 -0.0156 -0.0008 0.1	244 -0.0163 0	1415 0.307	0 0.4648										\vdash				F	
862 -0.0164 -0.0010 0.1	236 -0.0174 0	1411 0.307 1408 0.307					<u> </u>	 										
863 -0.0168 -0.0012 0.13 864 -0.0172 -0.0014 0.13		1404 0.307 1400 0.307								ļ		 		 	 	 	 	
865 -0.0177 -0.0015 0.1	223 -0.0192 0	1398 0,307	3 0.4662															
866 -0.0182 -0.0017 0.11 867 -0.0186 -0.0019 0.11	218 -0.0199 0	1.1392 0.307 1.1388 0.307			 	 	 	+	 	1	 	 	 	1	t	<u> </u>	<u> </u>	
868 -0.0190 -0.0021 0.1	210 -0.0210 0	1355 0.307	4 0.4889					Ţ	T		(-			1			1
869 -0.0193 -0.0022 0.11 870 -0.0198 -0.0023 0.11	202 -0.0216 0	0.1381 0.307 0.1378 0.307					<u> </u>								1			
871 -0.0201 -0.0025 0.1 872 -0.0205 -0.0025 0.1	199 -0.0226 0	0.1374 0.307 0.1371 0.307	8 0.4676			+		-			 -	 	1	1	+		 	1
873 -0.0200 -0.0026 0.1	191 -0.0237 0	0.307	7 0.4881								1==				 			
874 -0.0213 -0.0030 0.1 875 -0.0217 -0.0031 0.1	1831 -0.02481 0	0.1364 0.307 0.1360 0.30			 	-	 		 	1	+	 	 	+	1		 	1
576 -0.0221 -0.0032 0.1	179 -0.0254 0	0.30	0.4689			 						-	 	J				\Box
577 -0.0225 -0.0034 0.1 578 -0.0229 -0.0035 0.1		0.30 0.1351 0.30	0,4591	<u> </u>			1			<u> </u>		<u> </u>						
579 -0.0232 -0.0037 0.1	168 -0.0289 (0.1347 0.300 0.1344 0.300	0.4696			 			-		+	-	-				-	1
681 -0.0240 -0.0040 0.1	160 -0.0280 0	0.1340 0.30	0.4700															
582 -0.0243 -0.0041 0.1 583 -0.0247 -0.0042 0.1	157 -0.0284 0	0.30				 	1	1	-			 	 	1	 	 	 	┼
884 -0.0251 -0.0043 0.1	149 -0.0294 0	0.331 0.30	2 0.4707			1					 			1			ļ	
885 -0.0254 -0.0045 0.1 886 -0.0258 -0.0046 0.1	146 -0.0299 (0.1328 0.30 0.1324 0.30				-	 	+	1		1	 	 		1	 	 	
887 -0.0262 -0.0048 0.1	138 -0.0310 (0.1321 0.30	3 0.4714			1		1	1	1	T				1		-	==
865 40.0266 40.0049 0.1 859 40.0270 40.0061 0.1	130 -0.0321 6	0.30 0.1314 0.30				 	+	1	 	+	1-		 		1	1	-	
890 -0.0273 -0.0053 0.1	127 -0.0326 0	0.30	0.4721			Ţ		1		T					1	\Box		1
891 -0.0277 -0.0064 0.1 892 -0.0281 -0.0065 0.1	119 0.03361 0	0.1306 0.30 0.1304 0.30			<u> </u>	1			 	1		1	1	 	 	1	1	
893 -0.0285 -0.0057 0.1	115 -0.0342 (2.1301 0.30	0.472						1	\vdash	-	1	<u> </u>	 	 	<u> </u>	ļ	+
894 -0.0289 -0.0059 0.1 895 -0.0293 -0.0080 0.1	107 -0.0353 (0.1297 0.30 0.1293 0.30			<u> </u>		<u> </u>		<u> </u>	士二	1	1		1		<u> </u>		
696 -0,0297 -0.0062 0.1	103 -0.0359 0	0.1290 0.30 0.1286 0.30			-				1	F	4	-	\vdash	$\overline{}$			 	1
898 -0.0305 -0.0085 0.1	095 -0.0370 (0.1283 0.30	0.4741						1	1		1					1	
899 -0.0310 -0.0067 0.1 900 -0.0315 -0.0069 0.1	090 -0.0376 (0.1279 0.30 0.1274 0.30			1	1	1	1	 	 	1	 	 	+	 	 		+
901 -0.0320 -0.0071 0.1	080 -0.0391 (0.12691 0.30	0.4749			1		1=			 		1	1		=	 	
902 -0.0325 -0.0073 0.1 903 -0.0331 -0.0078 0.1		0.1264 0.30 0.1256 0.30	9 0.475	5	-	 	 	+	 	+	+	1	 	4		 	-	
904 -0.0337 -0.0079 0.1		0.1252 0.30	0.475	a)				1			3	T						\Box
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		я	C	О	E		G	H	7 7	7.7			М	N	0 1	P	0	R	s	77	U 1	V
905	A	-0.0061																				
906	-0.0348	-0.0063	0.1052	-0,0431	0.1243	0.3091																
907	-0.0356	-0.00851	0.1045	-0.0440	0.1237	0.3092	0.4769					(
906	-0.0382	-0.00001	0,1038	-0,0452	0.1230	0.3092	0.4773															
909	-0.0372	-0.0094	0.1028	-0.0488 -0.0481	0.1220	0.3092	0.4778				~											
911	-0.0302	-0.0099	0.1016	-0.0407	0.1210	0.3002	0.4790															
812	-0.0405	-0.0107	0.0995	-0.0512	0.1190	0.3095	0.4796															
913	-0.0419	-0.0114	0.0961	-0.0533	0.1177	0.3096	0.4805															
914	-0.0436	-0.0122	0.0984	-0.0558	0.1180	0.3097						!										
915	-0 0454	-0.0129	0.0048	-0.0583 -0.0606	0.1144	0.3098	0.4825															
918 917	-0.0477	-0.0136 -0.0139	0.0923	-0.0605		0.3100					······································		i									
918	-0.0467	-0.01341	0.0933	-0.0600	0.1133	0.3099	0.4833															
919	-0.0443	-0.0125	0.0957	-0.0568	0.1153	0.3098	0.4818														!	
920	-0.0424	-0.0119	0.0976	-0.0544	0,1169	0.3093	0.4805															
921		-0.0112			0.1162 0.1193	0.3094	0,4797								 							
923		-0.0104		-0.0498	0.1199	0.3093	0.4791															
924	-0.0389	-0.01031	0.1011	-0.0492	0,1203	0.3091	0.4766															
925		-0.0101		-0.0454	0,1207	0.3090	0.4752	ļ														
925 927		-0.0099 -0.0097		-0.0478 -0.0469	0.1211	0.3090	0.4779	<u> </u>	<u> </u>						I							
928		-0.0094					0.4774															
929		-0.0091		-0.0454	0,1227	0.3090	0.4771															
930	-0.0356	-0.0087	0.1044	-0.0443	0.1235	0.3090	0.4768														 	
831		-0.0084			0,1242	0,3091		 				<u> </u>		 	 			<u> </u>		 		
933		-0.0082			0,1245 0,1253	0.3091			 -	 				 				 -				
934		-0.0077		-0.0410		0.3089	0.4756	t														=
935	-0.0337	-0.0068	0.1063	-0.0424	0.1245	0,3002	0.4751															
938		-0.0079					0.4755		ļ					<u> </u>				<u> </u>		<u> </u>		
937		-0.0068			D.1202 0.1277	0,3095		}	 				·			 		 -		 	 	
938 939		-0.0063						}	 	 				l	 	 						
840	-0.0315	-0.0062	0.1065	-0.0377	0.1281	0,3096	0.4754															
941		-0.0059								L					 						 	
942		-0.0057							 -	 	·		 	 				ļ	<u> </u>			
943		-0.0058 -0.0057			0.1291			 		 				 	 		 			 	 	
945	-0.0295	-0.0058	0.1102						1	 												
946	-0.0298	-0.0055	0.1104	-0.0351	0.1297	0.3083	0,4741															
947		-0.0053				0.3003	0.4739	-	ļ		<u> </u>			! -	ļ	<u> </u>	ļ	ļ	ļ		 	/
948	-0.0295	-0.0061	0.1105	-0.0355	0.1291		0.4734	 	 	 					 			 	├	 	 	
050		-0.0051			0.1303	0.3096	0.4742	1	 	 	 			 	 			1	1			
961	-0.0288	-0.0044	0.1112	-0.0332	0.1312	0.3100	0.4743	1														
952	-0.0288	-0.0048	0.1112	-0.0336	0.1306	0.3096	0.4740					-						ļ	 	!	!	
963		-0,0049		-0.0337	0.1307	0.3094	0.4738			 		 	ļ	 	 	 	 	 -	├ ──		 	
85		-0.0047			0.1310	0.3090	0.4739	 	 		 -	 	 	 	 	 		 	 	 	 	 1
866	-0.0283	-0.0047	0.1117	-0.0330	0.1311	0.309	0.473	1														
957	-0.0282	-0.0048	0,1118	-0.0328	0.1313	0.3096	0.4730											-				
958		-0.0038							 		├ ──		ļ	 		 	 	ļ	 	ļ	 	├
959		-0.0035							 	 	}	 	 						 		 	
981	-0.0276	-0.0042	0.1124	-0.0318	0.1320					 	 			1				1				
962	-0.0274	11-0,0041	0.1120	-0.0314	0.1323	0.309																
983	-0.0272	2 -0.0039	0.1128	-0.0311	0.1325								ļ	 	 	 	 	<u> </u>	ļ	 	 	ļI
984	-0.0271	1 -0.0037	0.1125	-0.0306	0.1328				 	 	 			 		 	}	 		┼		
965	0.0261	-0.0034 7 -0.0034	0.1131	-0.0302	0.1333				1	 	 			 	+	 			 	 	 	1
967	-0.026	-0.0037	0.1133	-0.030	0.1330				1													
968	-0.0267	71-0 0040	0.1133	-0.0307	7 0.1326	0,309				1	1			1	ļ		 	 			 	├ ──
959	-0.0267	7 -0.0038	0.1133	-0.0305	0.1329	0.300			 	 	 	 	 	 	+	 	 	 	 	+	+	
970	-0.020	2 -0.0032	0.1130	-0.0202	0.1337	7 0.310			 	 		 	 	1	 	 	 	 	 	 	1	
972	-0.026	2 -0.0031	0.113	-0.029	0.1337	0.310																
973	-0.025/	2 -0.0031 9 -0.0026	0.1141	-0.0284	0,134				1	1			 	1			_		 		 	
974	0.025	7 -0.0023	0.1143	-0.0280	0,1348	0.310			 	}	 	 				 	 -		}	 	 	
976	-0025	≙i <u>-</u> ∩ ດດ27	0 1161	-000%	0.134	31 0.310			 	 	 	 	 	1	1	1	 	1	1	†	<u> </u>	
977	-0.025	6 -0.0024	0.114	-0.028	0.134	0.310																
978	-0.025	7 -0.0024	0.114	-0.028	0.1347	7]_0.310			1	-					+	 	 _			 	4	4
979	-0.025	81-0.0025	0.1144	-0.028	2 0.1340	5) 0.310			 	- 	1	 	 	 	 	 	} -	 	+	+	 	+
960	-0.025	8 -0.0026	0.114	-0.028	0.134				1	 	 	 	 	 	+	 	 	+	1	1		1
182	-0.025	0.0026	0.114	-0.026			2 0.473	0	1	1	1											
963	-0.025	8 -0.0026 7 -0.0026	0.114	-0.028	0.134	0.310	2 0.473	11			1				4			1	+	+	4	
984	-0.025	7 -0.0025	0.114	-0.026	2 0,134	7 0.310			 	 	 	 	 	├		 	+		+	+	 	
985	-0.025	7 -0.0024	0.114	-0.028	0.134 4 0.134	6 0.310 6 0.310	4 0.473 2 0.473			1	 	 	 	 	+	 	+	+	+	+	+	
967	9.025	8 -0.0026	0.114	-0.028	3 0.134	6 _ 0.310	2 0.473			 	1	1										
968	-0.025	8 -0.0028 7 -0.0028	0.114	-0.028	0.134	4 0,310	0 0.472											ļ	1	1		
969	-0.025	7 -0.0026	D.114	-0.028	3 0.134	0.310	2 0.473			 					+			 	 	+	4	
990	-0.025	5 -0.0027 8 -0.0026	0.114	0.005	0.134	6 0.310 5 0.310	1 0.472 2 0.473		 	1		 	 	 	+	+	 	 	 	+	+	
965	4025	6 -0.0026 7 -0.0027	0.114	-0.028	0.134	5 0.310				1	+	 	 	 	1	1		+	 	1	1	
993	-0.025	7 -0.0027	0.114	-0.028	4 0.134	4 0.310	2 0.473	0														=
994	-0.025	7 -0.0024	D.114	-0.028	1 0.134	8 0.310							1			1	 	4	 _	+		
995		1 -0.0027			6 0.134	2 0.310									+	+		+	}		+	
998	-0.025	8 -0.0024	0.114	-0.028	0.134	8 0.310 8 0.310			+		 	 	 	 		 	 	 	} -	 -	+	+
996	-0.020	7 -0.0024	0.114	-0.02B	4 0.134	41 0.310			 		1	 	+	+	 	 	1	1	1	1		
999	-0.025	0 -0.0026	0.114	-0.026	4 0.134	5) <u>0.310</u>	4 0.473	3		1												=
1000	-0.025	8 -0.0024	0.114	-0.026	2 0.134	7 0.310	6 0.473	5									1	1	1	4		+
1001	-0.025	5 -0.0025	0.114	0.020	01 0.134	71 0.310	3 0,473	01	1	.1	1	1	1	1	1			(·	1		